

Basic Electronics

Introductory Lecture Course for
**Technology and Instrumentation
in Particle Physics 2011**

**Chicago, Illinois
June 9-14, 2011**

Presented By

Gary Drake

Argonne National Laboratory

Session 3

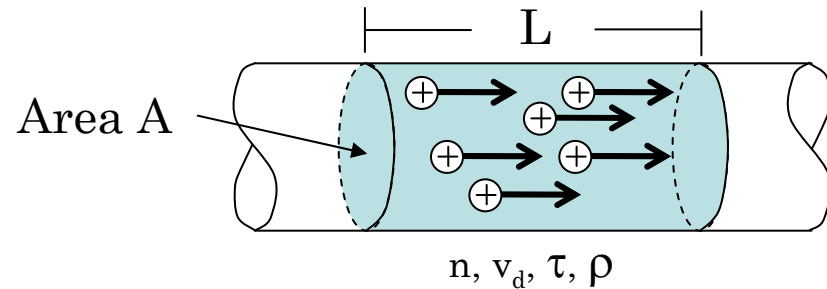
Session 3

Semiconductor Devices

Preliminary Concepts

Resistivity Revisited

$$R = \rho L / A$$



$$\rho = 1 / \sigma = 2 m / (n q \tau) \rightarrow \text{Units: Kg-meter}^3 / \text{Coulomb-sec}$$

= Ohm-meter
(or often, Ohm-cm)

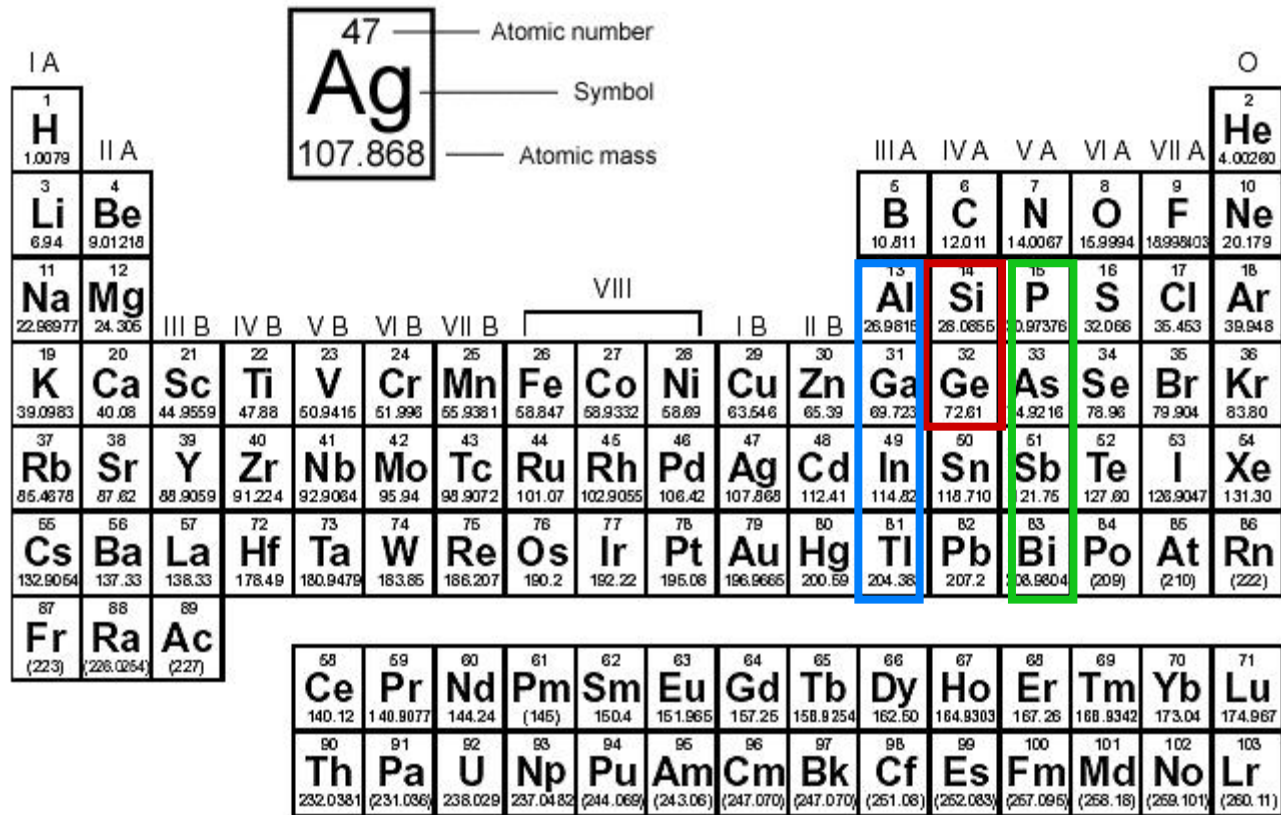
⇒ Only depends on physical properties

Resitivity of Materials

<u>Metals</u>	<u>Semiconductors</u>	<u>Insulators</u>
10^{-6} to 10^{-4} Ω -cm	10^{-3} to 10^{+8} Ω -cm	$> 10^{+8}$ Ω -cm
– Upper electron shells nearly empty	– Partially filled shells – Bonds covalently to form weakly stable structures	– Completely filled shells

Preliminary Concepts

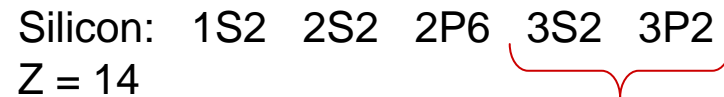
- Semiconductors on the Periodic Chart



Preliminary Concepts

Atomic Structure of Silicon – Group IVA

- Electron structure



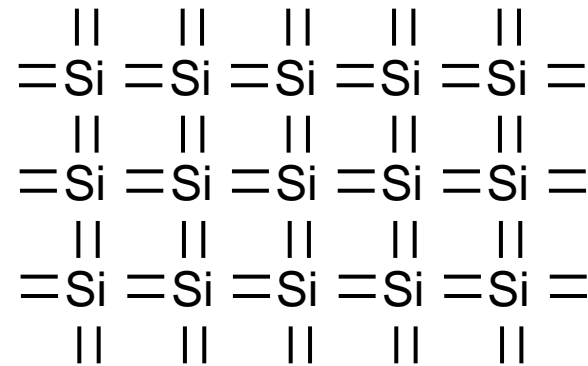
4 empty positions in the 3P shell

4 / 8 positions filled

- Represented as: $\begin{array}{c} | \\ -\text{Si}- \\ | \end{array}$ ← Each line is an electron in the 3rd shell

- Covalent Bonding

- ◆ Intrinsic silicon bonds covalently in a crystalline structure, sharing electrons with neighbors to completely fill the 3P shell

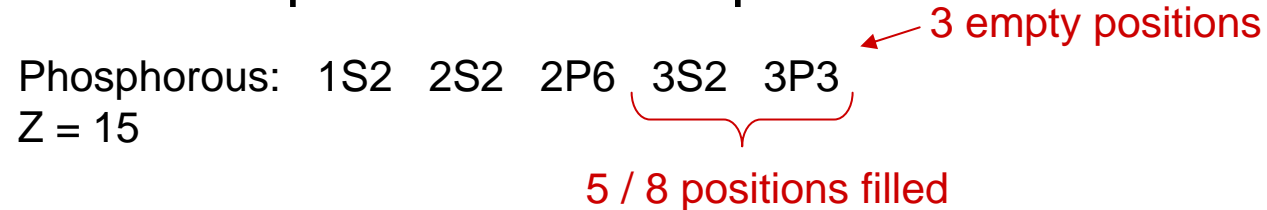


⇒ Bonds can break from thermal energy or E field to give mobile charge

Preliminary Concepts

- Adding Impurities into Silicon

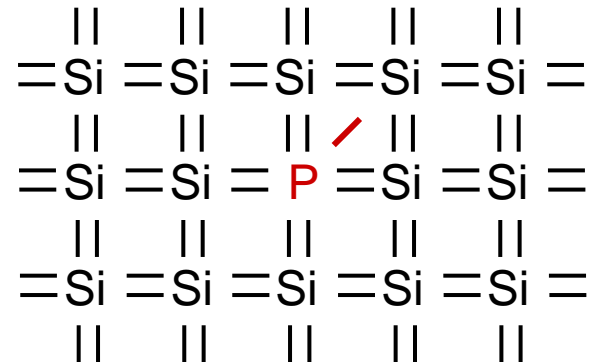
- Consider Phosphorous – Group VA



- Represented as: $\begin{array}{c} | \\ -P- \\ | \end{array}$ ← Each line is an electron in the 3rd shell

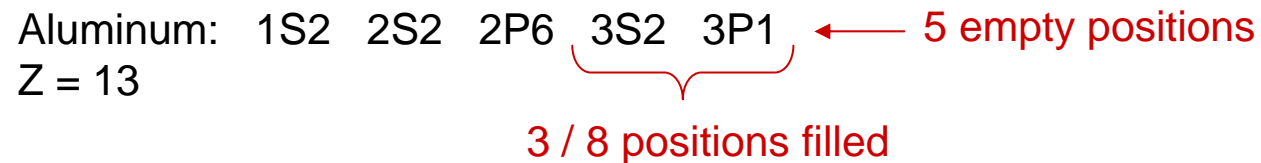
- Introduction into Silicon Crystalline Structure

- ♦ Extra electron is weakly bound, and easily removed
 → **Donor Impurity**



Preliminary Concepts

- Adding Impurities into Silicon (Continued)
 - Consider Aluminum = Group IIIA



- Represented as:

$$\begin{array}{c} - \text{Al} - \\ | \end{array}$$

 ← Each line is an electron in the 3rd shell

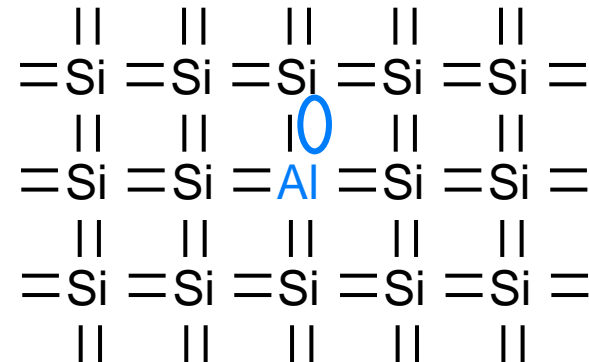
- Introduction into Silicon Crystalline Structure

- ◆ Missing electron is weakly accepted into lattice

→ **Acceptor Impurity**

- ◆ Concept of mobile **“holes”**

- When electron is captured, hole moves from location to location



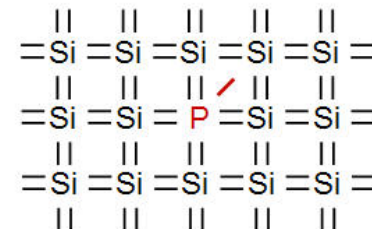
Preliminary Concepts

■ Adding Impurities into Silicon (Continued)

- Introduction of impurities into intrinsic silicon is called **“Doping”**
- Amount of doping characterized by concentration of charge carriers
 - ◆ n_i = # intrinsic carriers in pure silicon / unit volume $\approx 1.4E10 / \text{cm}^3$
 - ◆ N_d = # donor atoms / unit volume @ 300° K
 - ◆ N_a = # acceptor atoms / unit volume

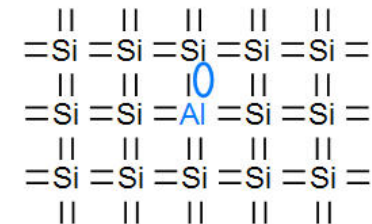
• **N-type Silicon**

- ◆ $N_d - N_a \gg n_i$
 - High concentration of donor atoms
 - Provides excess electrons to lattice as mobile charge carriers



• **P-type Silicon**

- ◆ $N_a - N_d \gg n_i$
 - High concentration of acceptor atoms
 - Provides excess holes to lattice as mobile charge carriers



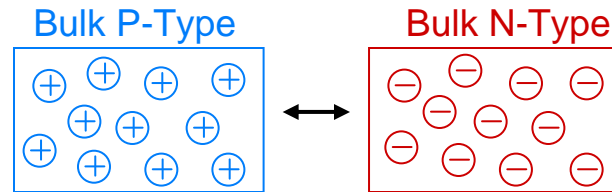
Preliminary Concepts

- Adding Impurities into Silicon (Continued)
 - How to make use of mobile charge carriers
 - ◆ Bonds can be broken by:
 - Application of an Electric Field
 - » Basic principle of how integrated circuits work
 - Application of Light → Photons impart energy
 - » Basic principle of how photo cells work
 - » Use reverse principle for light emitting diodes (LEDs)
 - Heat → Kinetic Energy
 - » Basic use for temperature sensors
 - » Generally a bad property for semiconductors...

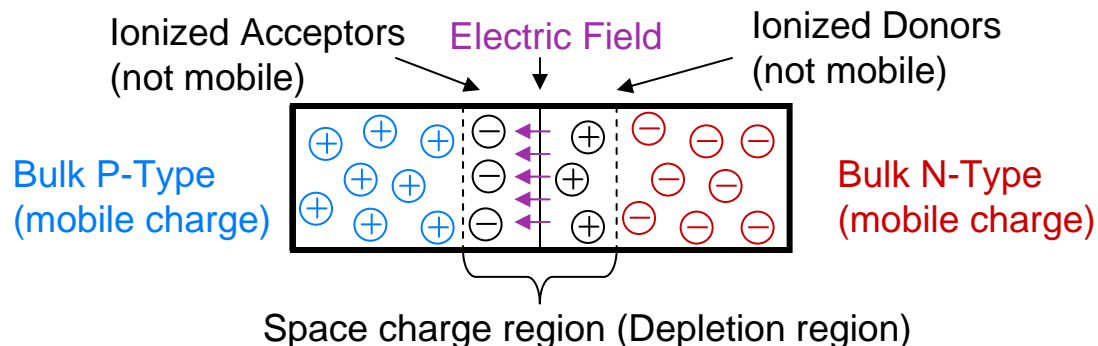
PN Junctions

■ Forming a PN Junction

- Take P-type & N-type silicon, and butt them together



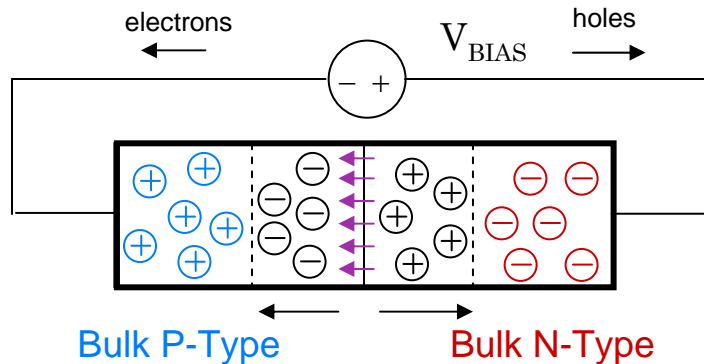
- When butt together, opposite charges attract
 - ◆ Mobile electrons from N-type silicon attracted to vacancies in P-type
 - ◆ Mobile holes from P-type silicon attracted to vacancies in N-type
 - ⇒ **Results in Acceptor & Donor atoms being ionized**
 - ⇒ **Creates space charge regions**
 - ⇒ **Results in the creation of a built-in Electric Field**



PN Junctions

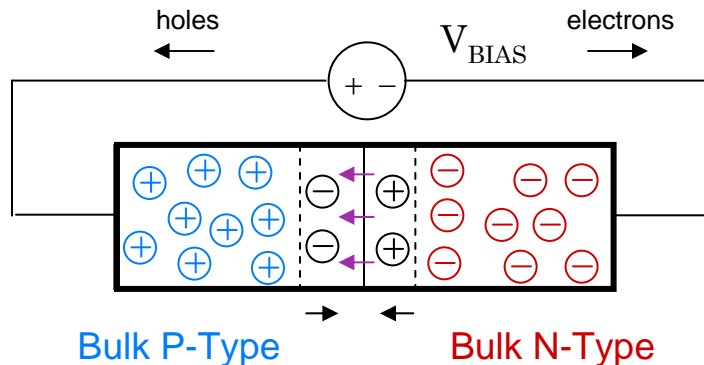
■ Biasing a PN Junction

- Suppose apply a voltage to the PN Junction



- ◆ Positive terminal of V_{BIAS} attracts electrons
 - ◆ Negative terminal of V_{BIAS} attracts holes
 - ◆ Makes space charge region bigger
 - ◆ Increases E field across junction
 - ◆ Reduces ability of current to flow across junction
- ⇒ **Reverse Bias**

- Now suppose we reverse the polarity of V_{BIAS}

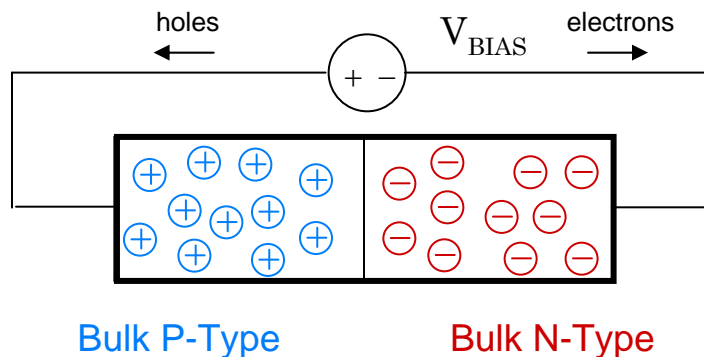


- ◆ Positive terminal of V_{BIAS} adds holes to P region
 - ◆ Negative terminal of V_{BIAS} adds electrons to N
 - ◆ Makes space charge region smaller
 - ◆ Decreases E field across junction
 - ◆ Enhances ability of current to flow across junction
- ⇒ **Majority Carrier:**
Holes recombine with ionized acceptors
Electrons recombine with ionized donors

PN Junctions

■ Biasing a PN Junction (Continued)

- At a critical bias, space charge region disappears



- ◆ Built-in E field across junction is gone
- ◆ Now charge carriers provided by V_{BIAS} can move across PN junction
- ⇒ **Forward Bias → Conduction**
- ⇒ **Each new electron/hole pair pushes existing pair out of bulk**

- How much voltage is required to reach forward bias?

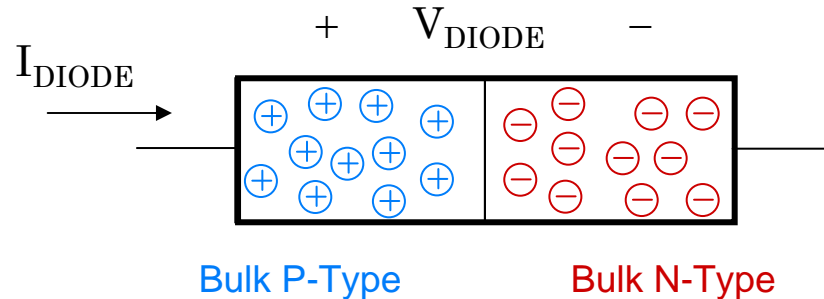
- ◆ Answer: Related to how much energy is required to remove bound electrons (or holes) from their nuclei
→ Work Function
 - Depends on doping concentrations
 - Depends on intrinsic carrier concentration
 - Depends on temperature

$$\phi = kT/q \ln [N_d N_a / n_i^2]$$

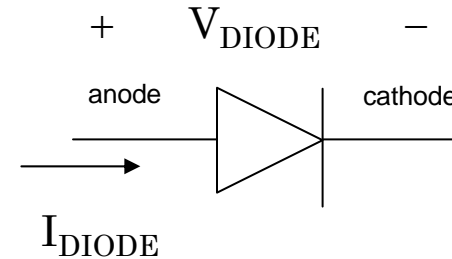
Diodes

- Physical Description

- Essentially a simple PN Junction



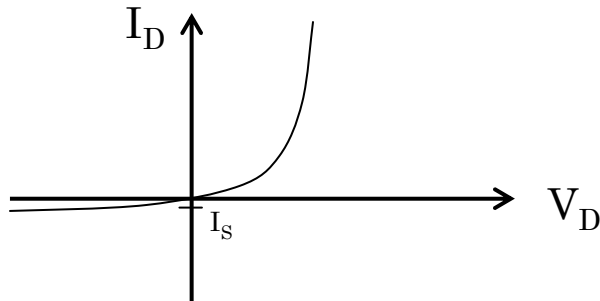
- Symbol



- IV Characteristics

- Shockley Diode Equation

$$I_D = I_S [e^{k V_D / (n q T)} - 1]$$



⇒ Nonlinear IV relationship

Where: I_S = Reverse Saturation Current
 k = Boltzman Constant (1.38E-23 J/K)
 T = Temperature (° Kelvin)
 q = charge (1.6E-19 C/e⁻)
 n = quality factor, $1 \leq n \leq 2$

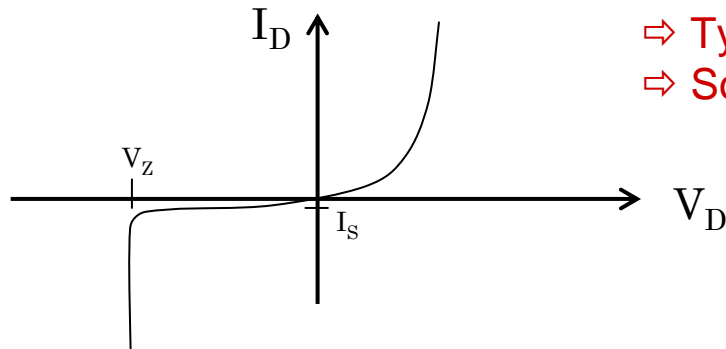
$$V_T = k T / q = 25.8 \text{ mV @ room temp} \\ = \text{Thermal Voltage}$$

⇒ In most diodes, I_S is very small

Diodes

■ IV Characteristics (Cont.)

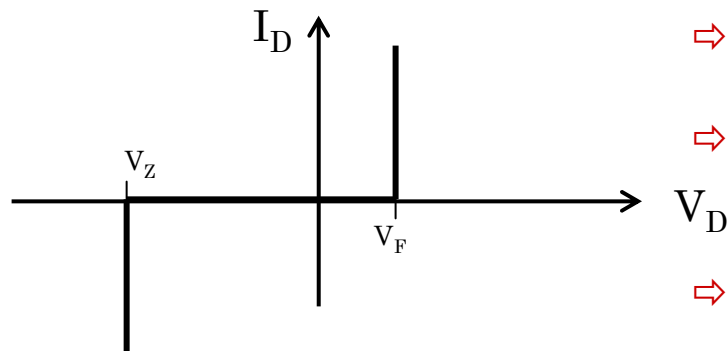
- Many diodes exhibit reverse breakdown → Zener Effect



- ⇒ Typical values: $V_Z \sim 5V - 15V$
- ⇒ Sometimes used for voltage references

• Ideal Characteristics

- ◆ Sometimes, it is useful to use a linear approximation

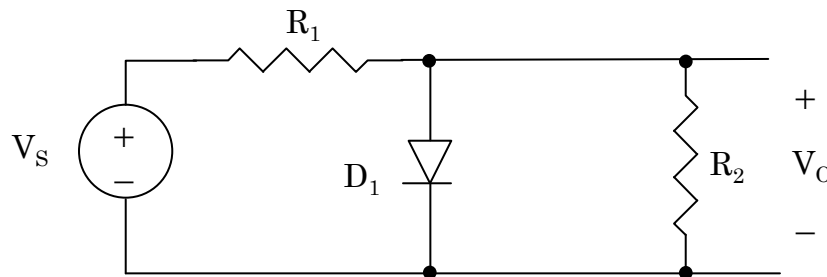


- ⇒ Typical values $V_F \sim 0.6V - 0.7V$ for Si
→ Looks like Voltage Source!
- ⇒ Approximates current flow in one direction only
- ⇒ Looks like a switch!

Diodes

■ Circuits

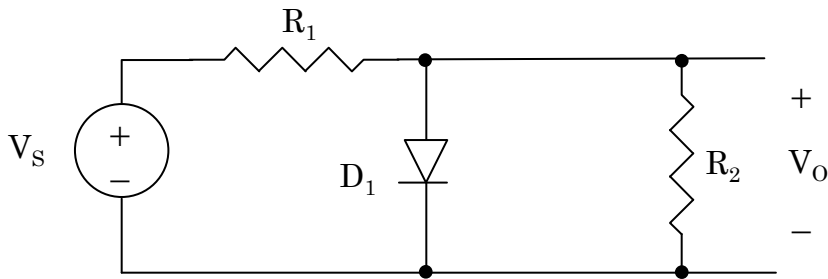
- Rarely use Shockley equation in hand calculations
- SPICE uses Shockley equation or behavioral models
 - ◆ Gives accurate solution
- For hand calculations – 2 methods:
 - ◆ Use linear approximation
 - ◆ Use graphical techniques



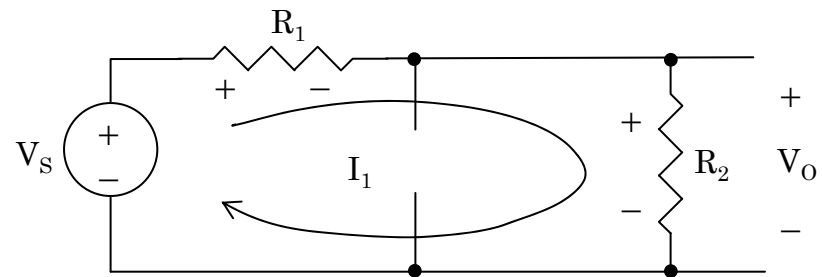
Diodes

- Circuits (Continued)

- Example – Use Linear Approximation:



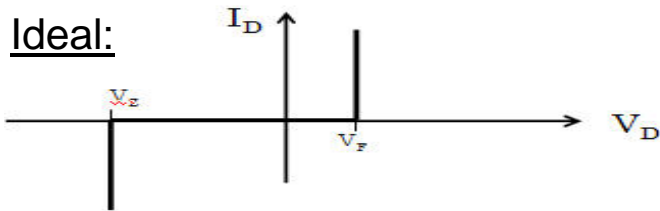
If diode is OFF:



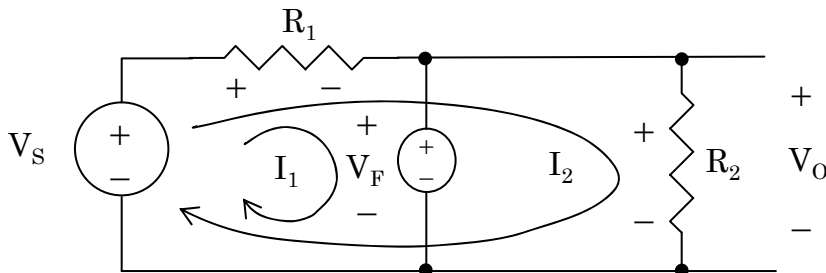
$$V_O = V_S R_2 / (R_1 + R_2)$$

Valid for: $V_O < V_F$

$$\text{Or: } V_S < V_F [1 + (R_1 / R_2)]$$



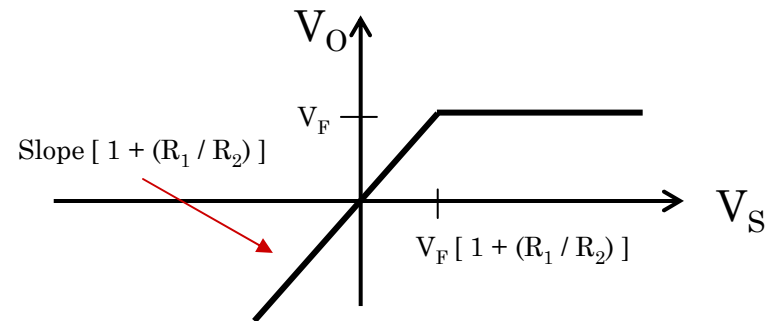
If diode is ON:



$$V_O = V_F$$

Valid for: $I_1 > 0$

$$\text{Or: } V_S > V_F [1 + (R_1 / R_2)]$$

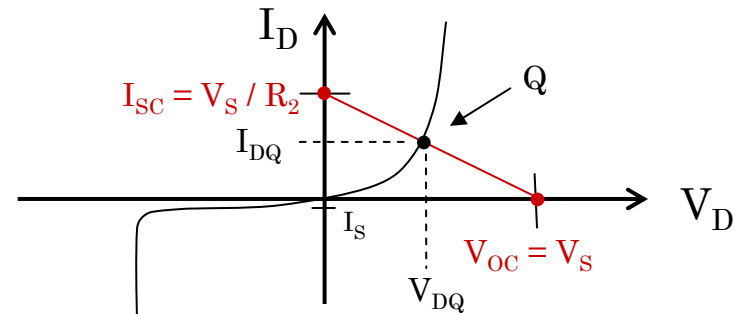
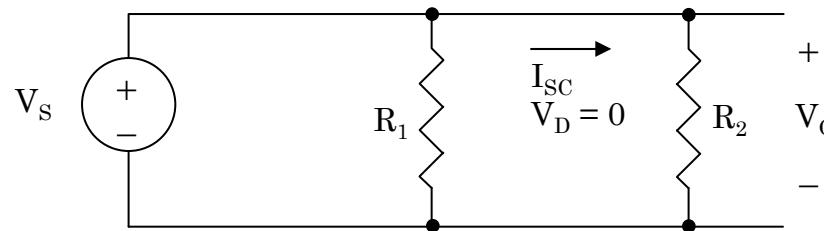
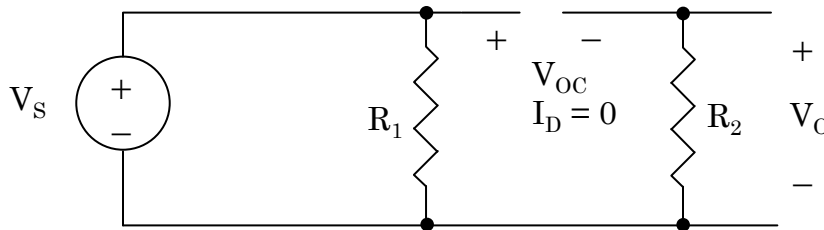
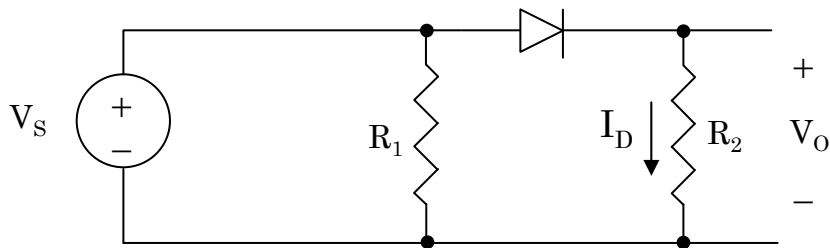


⇒ Called a Clamp Circuit

Diodes

■ Circuits (Continued)

- Example – Use Graphical Methods → Load Line Analysis:
 - ◆ Take Diode out – Calculate open-circuit voltage → $I_D = 0$
 - ◆ Then replace diode with short – Calculate short circuit current → $V_D = 0$
 - ◆ Plot on diode IV graph → Find Operating Point Q



$$V_{OC} = V_S$$

Then:

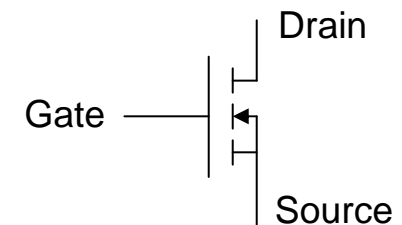
$$V_O = I_{DQ} R_2$$

⇒ Don't always have the IV curves for particular diodes...

Field Effect Transistors

■ Introduction

- Field Effect Transistors (FETs) are 3-terminal devices, where the current flow between two of the terminals (Drain & Source) is controlled through the use of an electric field applied at the third terminal (Gate), which modulates a conduction channel between the two active terminals.
 - ◆ Current flow is achieved by drift currents through the channel
 - ◆ Charge carriers are majority carriers (p-type → holes, n-type → electrons)
 - ◆ Current flow is uni-directional



- Several different kinds:

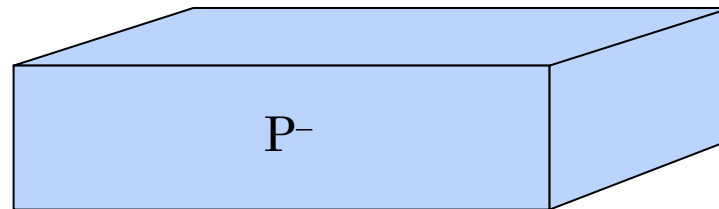
- ◆ Metal Oxide Semiconductor FET (MOSFET)
- ◆ Junction FET (JFET)
- ◆ Metal Oxide Semiconductor FET (MESFET)
- ◆ High Electron Mobility Transistor (HEMT)
- ◆ Depleted FET (DEPFET)
- ◆ (Many other variations...)

← We will focus on this today
⇒ Used extensively in HEP
⇒ Custom ASIC design!

MOSFETs

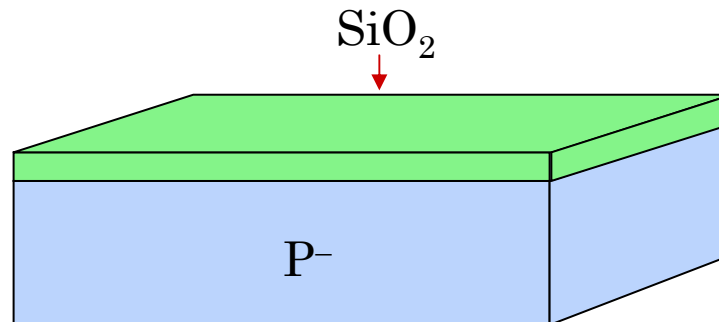
■ Basic Construction

- Begin with lightly-doped P-type substrate (could be N-type as well...)



- Cover surface with layer of silicon dioxide (SiO₂)
 - ◆ Like glass
 - ◆ Insulator → Very high resistivity → $\rho \sim 1E18 \Omega\text{-cm}$

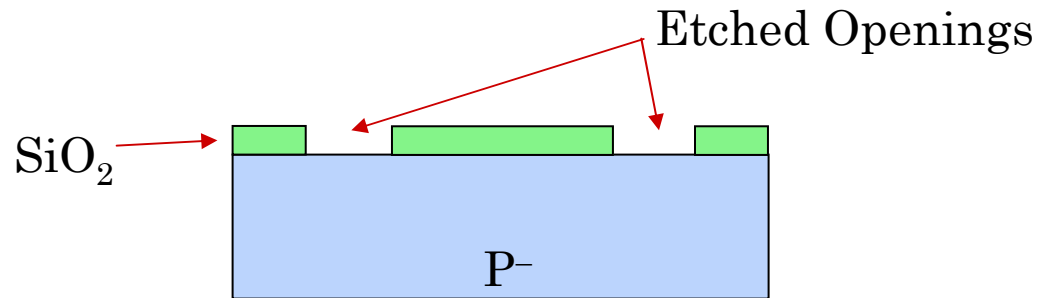
⇒ Very Important Aspect!



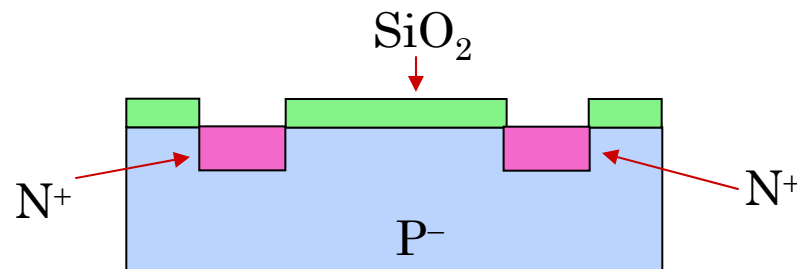
MOSFETs

■ Basic Construction (Continued)

- Etch openings into the SiO_2 using hydrofluoric acid (HF)
 - ◆ Dissolves SiO_2 but not the silicon underneath



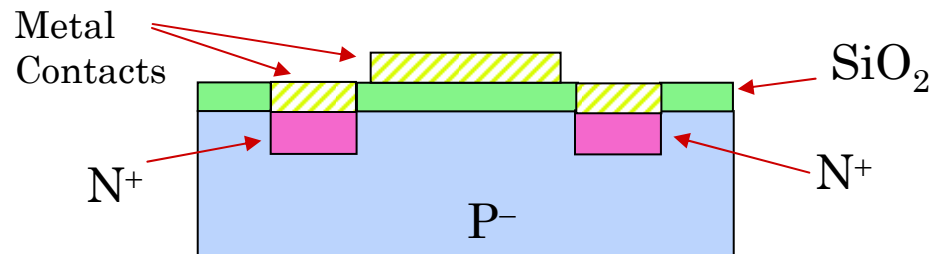
- Diffuse donor impurities into substrate to make N-type implants
 - ◆ Heavy doping $\rightarrow \text{N}^+$



MOSFETs

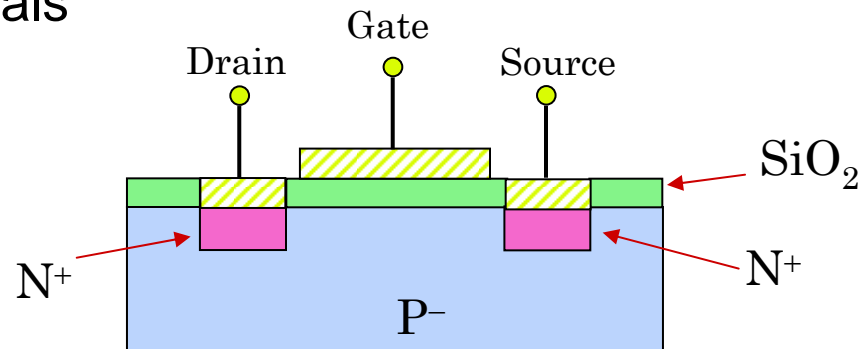
■ Basic Construction (Continued)

- Add metal contacts
 - ◆ Applied using Sputtering or Evaporating Metal



- Basic construction done
 - ◆ All process steps done with masks → lithography

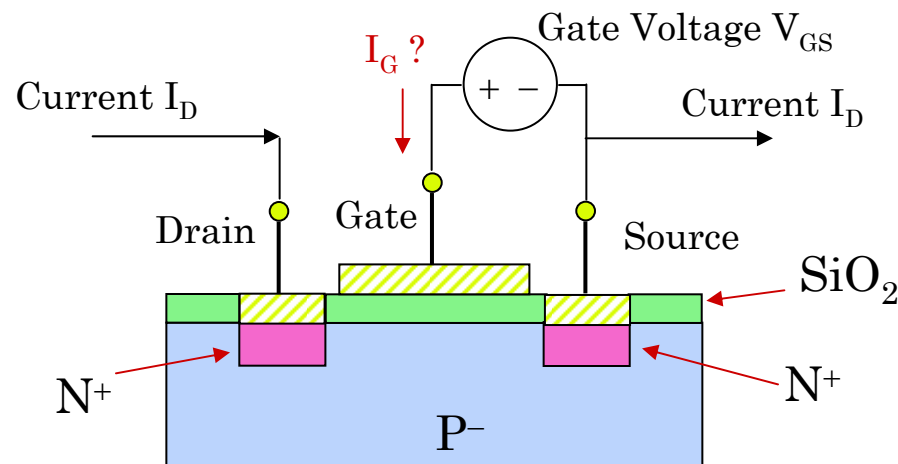
- Define terminals



MOSFETs

■ Basic Operation

- Idea is to use the Drain and Source terminals for conduction, and to control the flow of current through these terminals by applying a voltage to the Gate



⇒ Current $I_G = 0$
due to SiO₂

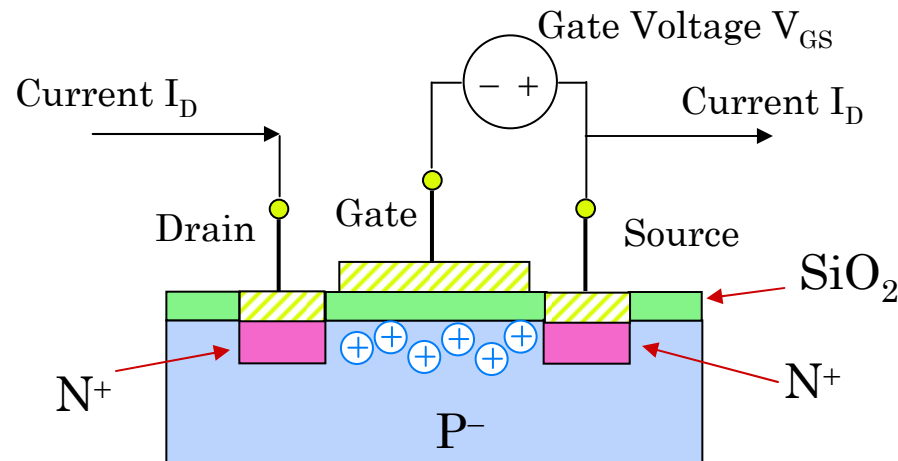
- There are three states of operation:
 - ◆ Accumulation
 - ◆ Depletion
 - ◆ Inversion

MOSFETs

■ Basic Operation (Continued)

• **Accumulation**

- ◆ Occurs when Gate voltage creates an electric field in the region between the N wells that attracts majority carriers → holes
- ◆ To attract holes in a P-type substrate, use a negative gate voltage



- ◆ The electric field lines from the Gate terminate on the accumulated holes, so that there is no attraction of electrons from the Drain and Source regions

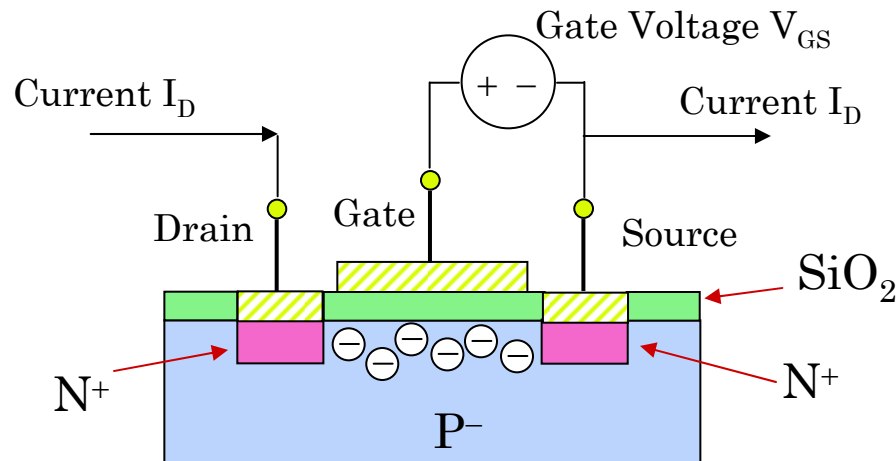
⇒ Results in no current flow between Drain and Source

MOSFETs

■ Basic Operation (Continued)

• **Depletion**

- ◆ Occurs when Gate voltage creates an electric field in the region between the N implants that repels majority carriers → holes
- ◆ To repel holes in a P-type substrate, use a positive gate voltage



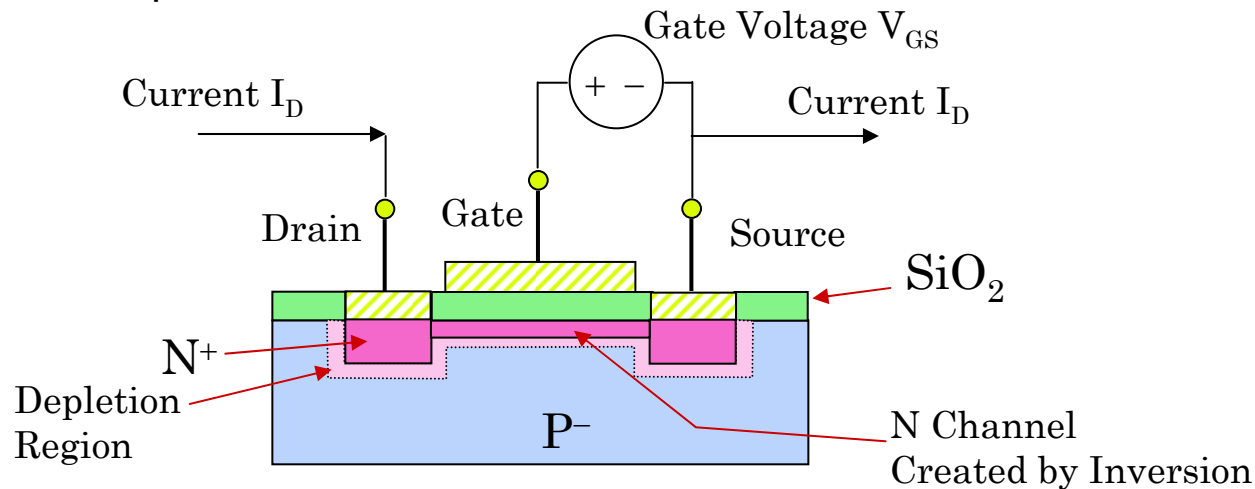
- ◆ Note that charge under Gate region is fixed charge, created by removing holes from their acceptor atoms in the P substrate
 - ◆ The electric field lines from the Gate terminate on the depleted acceptor atoms
- ⇒ Results in no current flow between Drain and Source

MOSFETs

■ Basic Operation (Continued)

• **Inversion**

- ◆ Occurs when Gate voltage reaches a critical point, where electrons begin to be attracted from N⁺ Drain and Source regions
 - Forms an N-type channel between the Drain and Source
 - Density of electrons in the channel ~ density of donor atoms in the N⁺ implants



- ◆ Now can have flow of electrons from Drain to Source
- ◆ Current flow is controlled by the Gate Voltage
- ◆ The point at which the Gate voltage creates a conductive channel under the Gate is called the Threshold Voltage V_{Th}

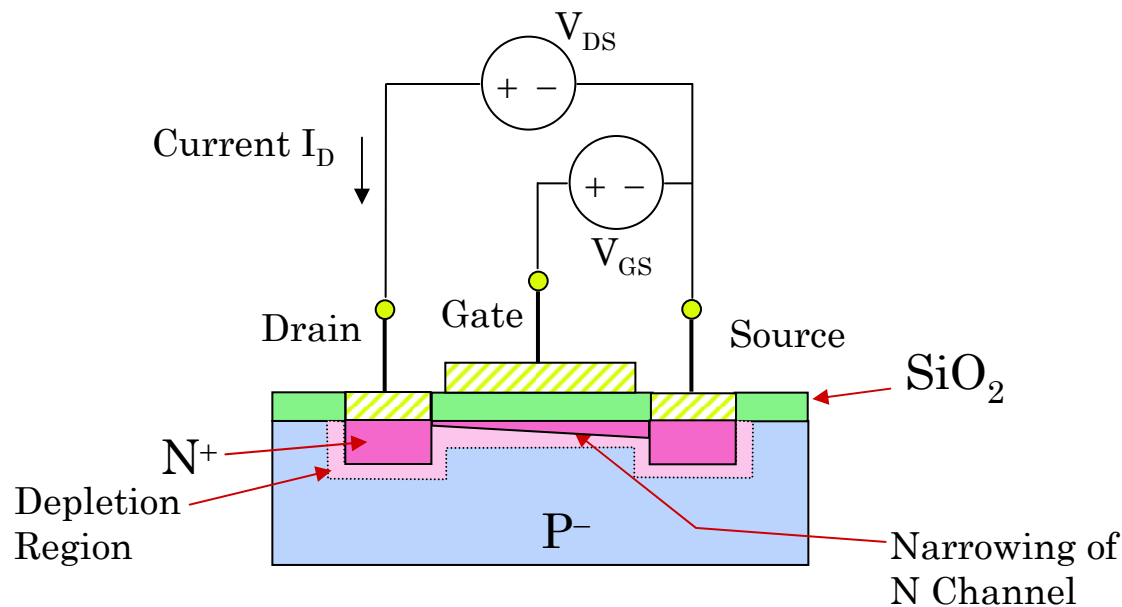
$$V_{GS} \geq V_{TH}$$

MOSFETs

■ Basic Operation (Continued)

• **Inversion** (Continued)

- ◆ Suppose now connect a voltage source between Drain and Source
 - Allows current to flow between Drain and Source
 - Results in voltage drop across channel
 - Channel begins to narrow at Drain end



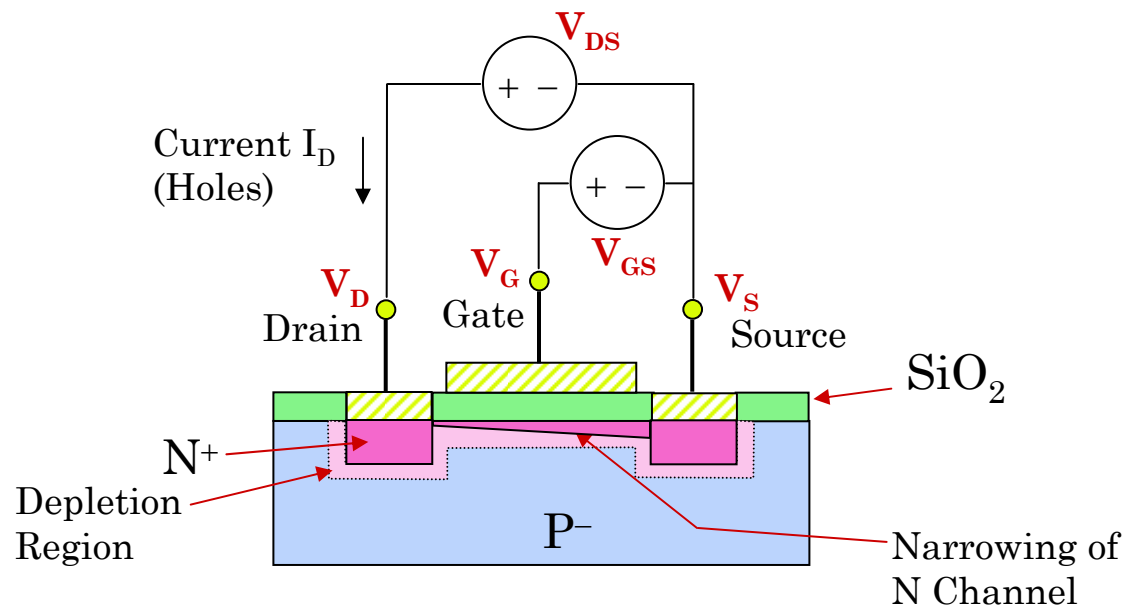
- Holes pumped into the Drain recombine with ionized acceptors in the channel near the Drain
- Electric field from the Gate is not strong enough to sustain the full width of the channel at the Drain, resulting in a narrowing of the channel

MOSFETs

■ Basic Operation (Continued)

• **Inversion** (Continued)

- ◆ If there is a voltage drop across the channel, then the voltage at the drain must be greater than at the source:



For the channel to exist:

$$V_{GS} > V_{TH}, \quad V_{GD} > V_{TH}$$

Then:

$$V_{GD} = V_{GS} + V_{SD} > V_{TH}$$

Or:

$$V_{DS} < V_{GS} - V_{TH}$$

- It can be shown that, for this mode of operation, the voltage drop in the channel is resistive, and that the current I_D is given by:

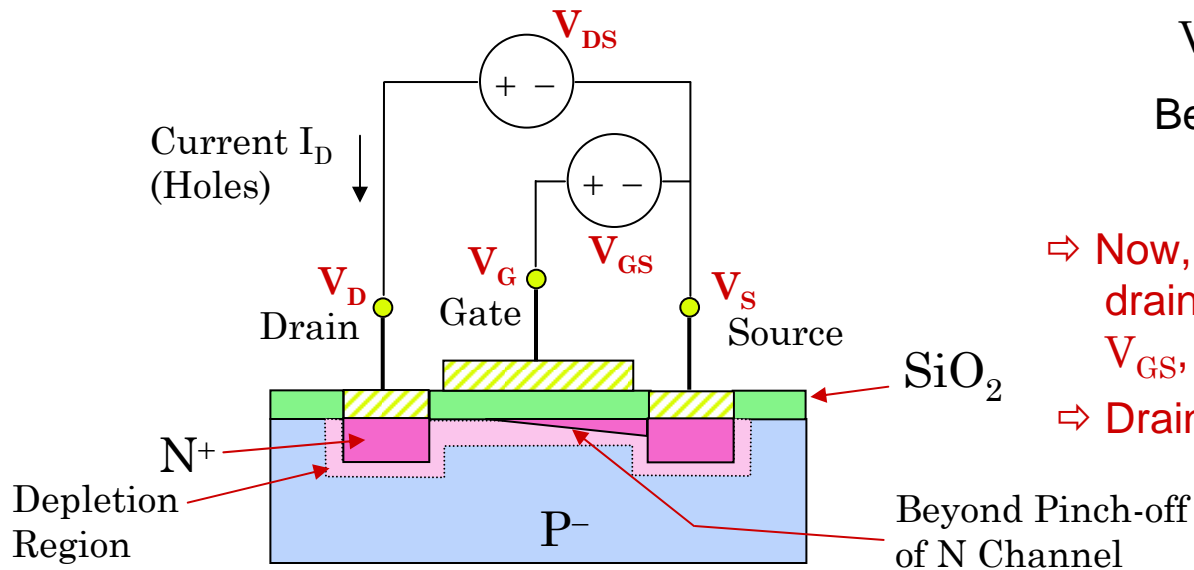
$$I_D \approx K V_{DS} [V_{GS} - V_{TH}], \text{ valid for } V_{DS} < V_{GS} - V_{TH}$$

MOSFETs

Basic Operation (Continued)

Inversion (Continued)

- As continue to increase V_{DS} , channel reaches a point where the width goes to 0 at the Drain → **Pinch-Off**
- As continue to increase V_{DS} , channel begins to recede at the Drain → **Beyond Pinch-Off**



At Pinch-off:

$$V_{DS} = V_{GS} - V_{TH}$$

Beyond Pinch-off:

$$V_{DS} > V_{GS} - V_{TH}$$

- ⇒ Now, current flow from drain to source depends only on V_{GS} , not on resistance in channel
- ⇒ Drain looks like current source!

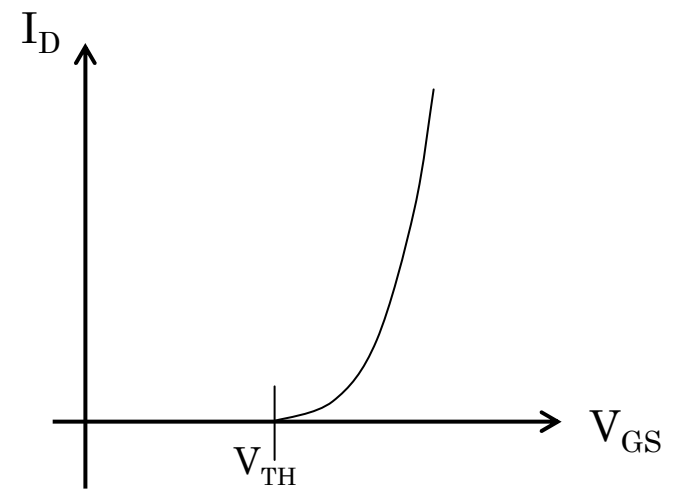
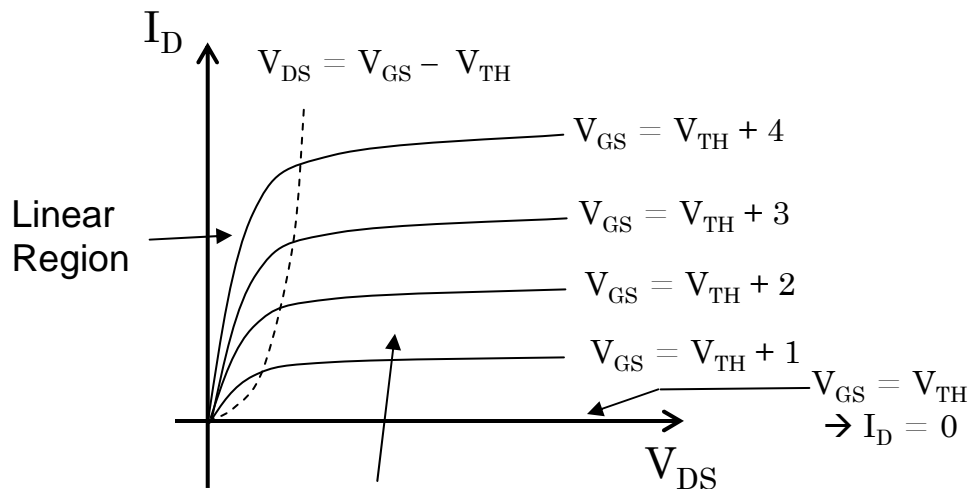
- It can be shown that for Beyond Pinch-off, the Drain looks like a current source, independent of V_{DS} , and that the current I_D is given by:

$$I_D \approx K/2 (V_{GS} - V_{TH})^2, \text{ valid for } V_{DS} \geq V_{GS} - V_{TH}$$

MOSFETs

■ IV Characteristics

- Have defined 2 regions of operation
 - ◆ Linear region → IV characteristics look resistive → Voltage-controlled resistor
 - ◆ Beyond Pinch-off → IV characteristics look like a current source
- Typically plot I_D versus V_{DS} as a function of V_{GS} ⇒ Family of curves



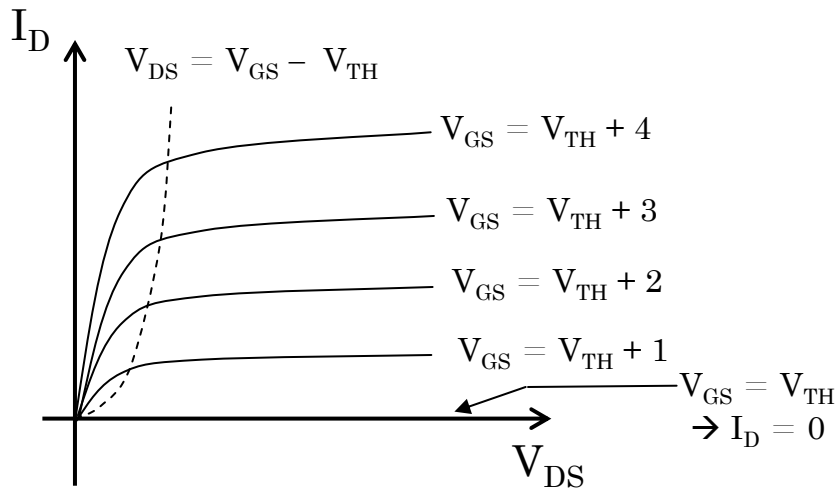
I_D vs V_{GS} in the Active Region

- Linear Region: $I_D = K V_{DS} [V_{GS} - V_{TH}]$, valid for $V_{DS} < V_{GS} - V_{TH}$
- Active Region: $I_D = K/2 (V_{GS} - V_{TH})^2$, valid for $V_{DS} \geq V_{GS} - V_{TH}$

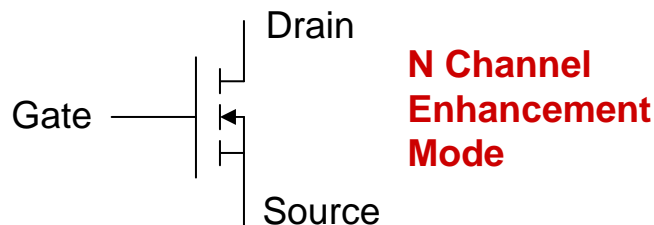
MOSFETs

Types of N-Channel MOSFETs

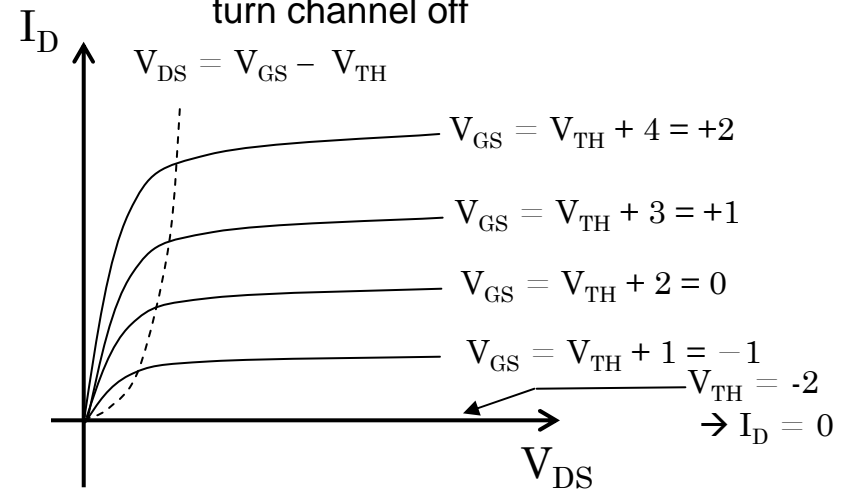
- Enhancement Mode FETs
 - ◆ Channel does not exist at $V_{GS} = 0$
 - This is what has been described previously
 - Must provide bias V_{GS} to create channel



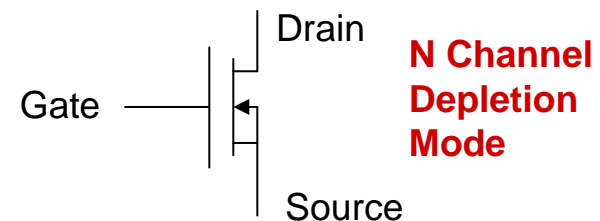
◆ Electrical Symbol



- Depletion Mode FETs
 - ◆ Channel does exist at $V_{GS} = 0$
 - These devices are made this way through doping the channel
 - Must provide negative bias V_{GS} to turn channel off



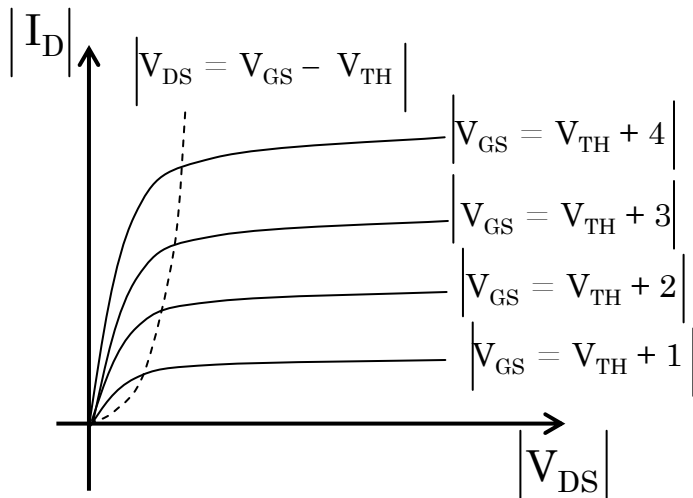
◆ Electrical Symbol



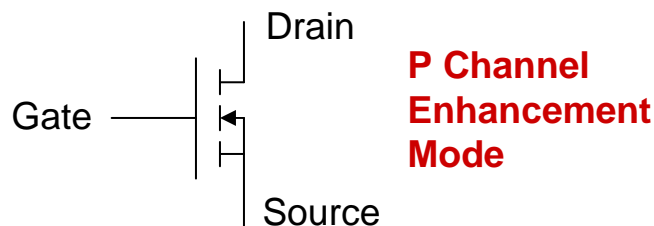
MOSFETs

- Types of P Channel MOSFETs \Rightarrow Everything is reversed...
 \Rightarrow Same plots, just use absolute value signs...

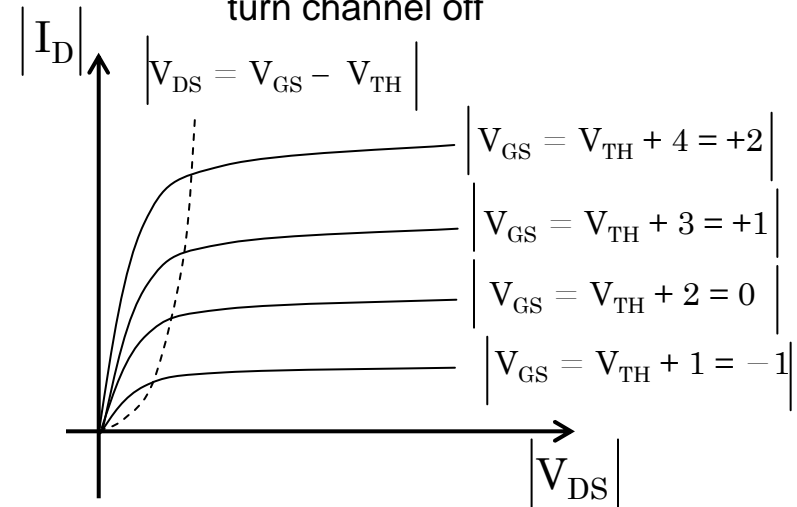
- Enhancement Mode FETs
 - Channel does not exist at $V_{GS} = 0$
 - Must provide bias V_{GS} to create channel



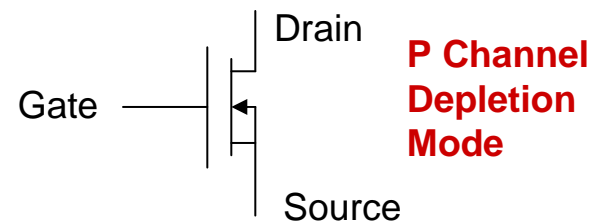
- Electrical Symbol



- Depletion Mode FETs
 - Channel does exist at $V_{GS} = 0$
 - Must provide negative bias V_{GS} to turn channel off



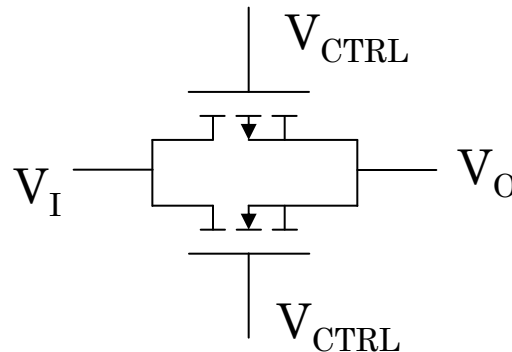
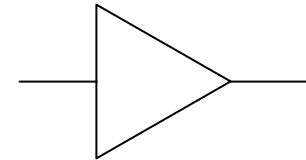
- Electrical Symbol



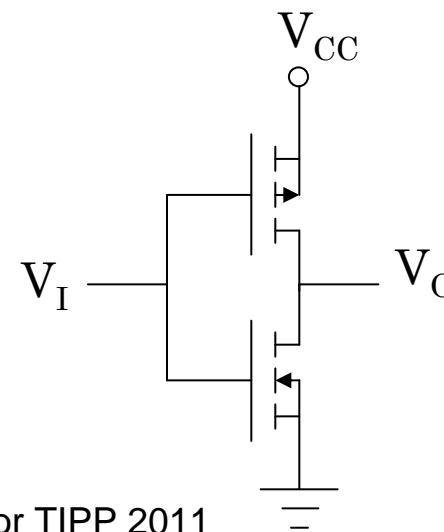
MOSFETS

■ Circuit Applications

- Linear circuits → Amplifiers
 - ◆ Voltage-controlled current source with gain
 - ◆ Excellent when need high input impedance
- Analog Switches



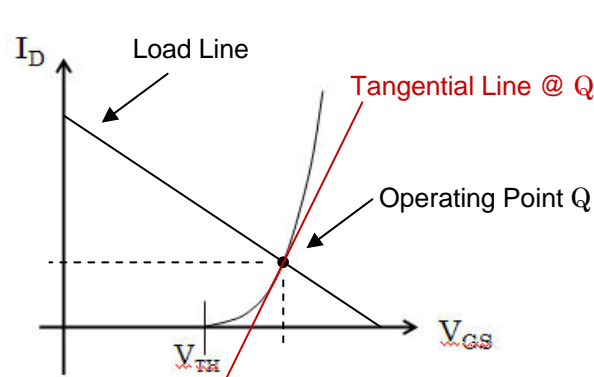
- Digital Logic → CMOS



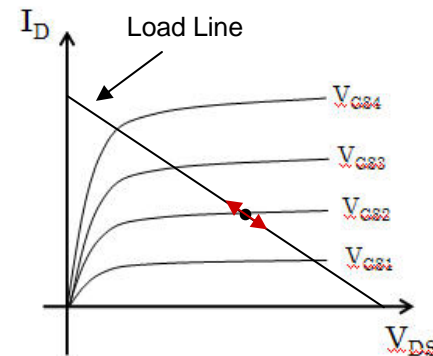
MOSFETs

Linear Circuit Models (N channel Enhancement Mode)

- Properties:
 - ◆ High impedance between Gate and Source
 - ◆ In Active Region, Drain-Source looks like a voltage-controlled current source
 - ◆ Generally, there are two types of models:
 - DC biasing
 - AC performance
- General Approach
 - ◆ Find DC operating point
 - ◆ AC parameters found from small excursions around operating point



AC Transconductance: $g_m = \left. \frac{\partial I_D}{\partial V_{GS}} \right|_Q$
 Found at Operating Point Q

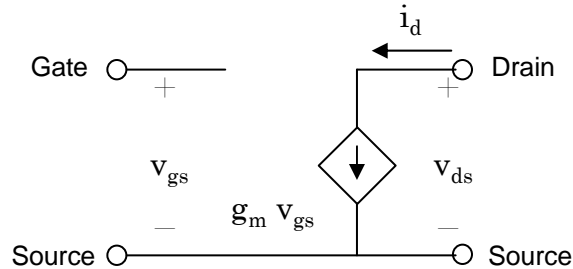
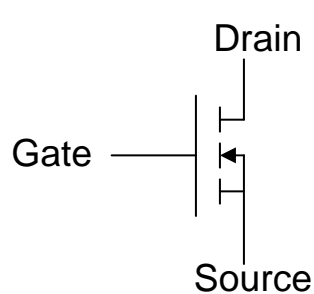


Generally, AC response occurs at small deviations around Operating Point

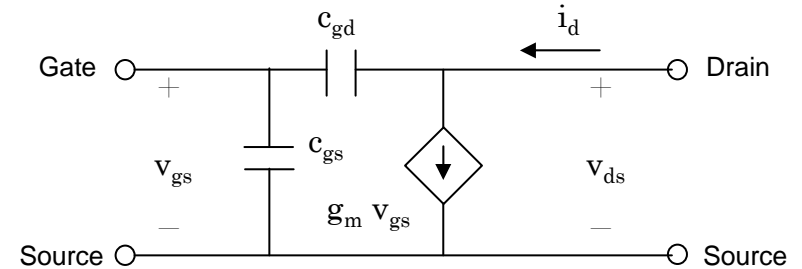
⇒ **Output will be the sum of the DC operating point + the AC response**

MOSFETs

- Linear Circuit Models (N channel Enhancement Mode) (Continued)
 - AC Model (assumes operation in active region)
 - ◆ Includes voltage-dependent current source with transconductance g_m
 - ◆ Sometimes includes parasitic capacitances between Gate and Drain c_{gd} , and between Gate and Source c_{gs}
- ⇒ Usually, FET parameters are supplied by the manufacturer



Mid-Frequency AC Model

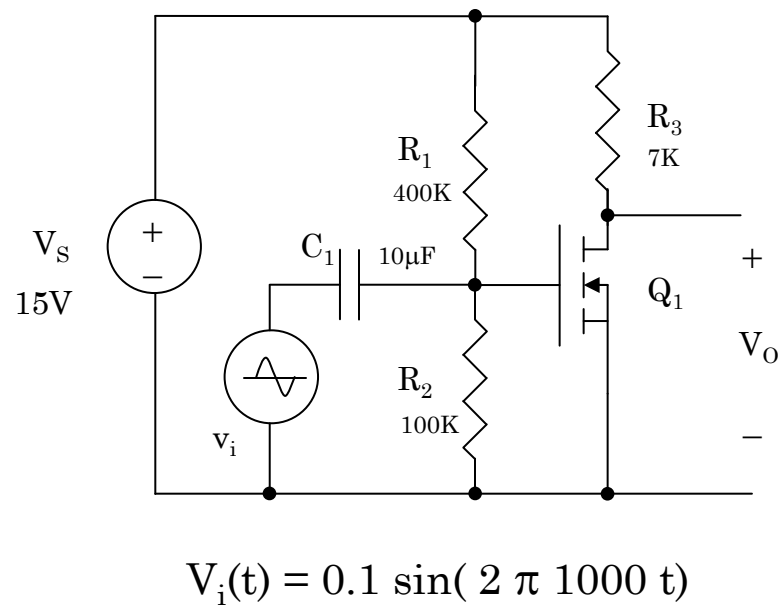


High Frequency AC Model

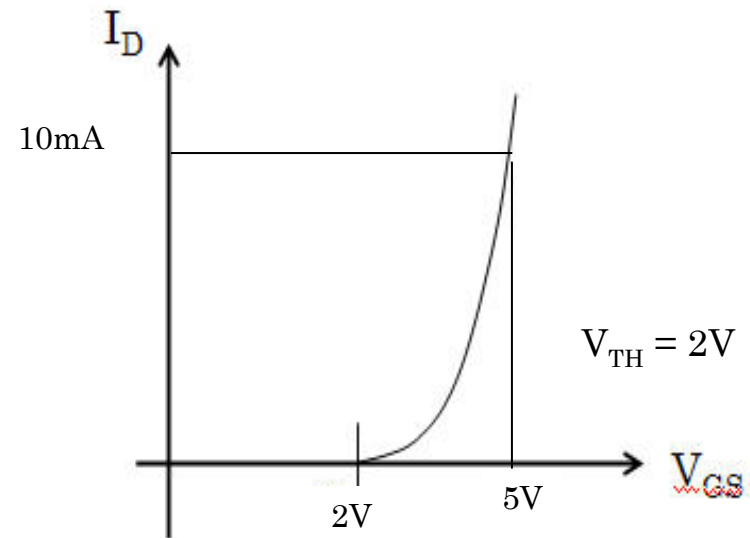
- Spice Models
 - ◆ Level 2: Use equations
 - ◆ BSIM: Behavioral
 - Much more accurate
 - Takes advantage of knowing process parameters
 - Used extensively for ASIC design

MOSFETs

- Linear Circuits
 - Example – Common Source Amplifier – N-channel, Enhancement Mode



Data from Manufacturer



MOSFETs

Linear Circuits

• Example – Amplifier

♦ DC Analysis – Find Q Point

- Remove all L's & C's
 - > Capacitors open
 - > Inductors short
- Remove all time-dependent sources
 - > Voltage sources shorted
 - > Current sources open
- Insert DC model
- Analyze circuit
- Find operating point

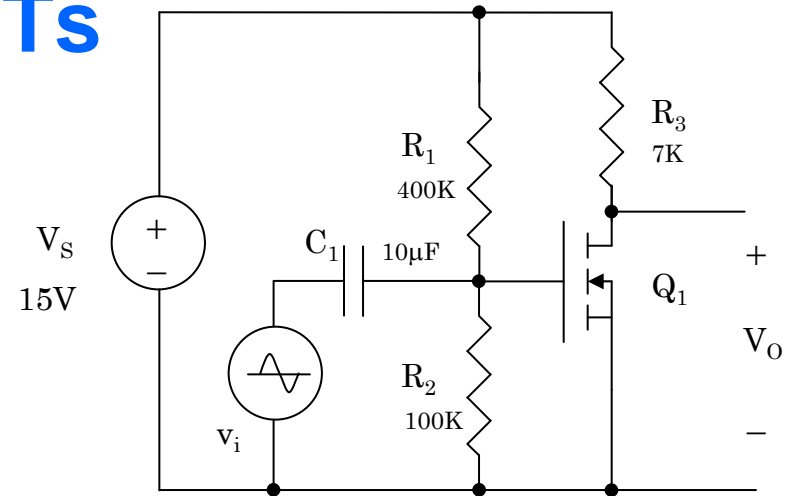
♦ In general, there is not a DC Model

- In Beyond Pinch-off, operating point is nonlinear

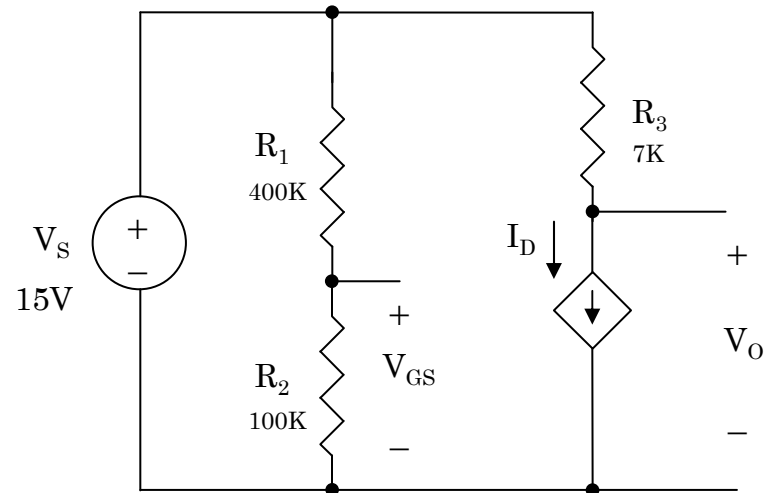
- > Must find operating point using info from manufacturer

$$I_D = K/2 (V_{GS} - V_{TH})^2$$

, valid for $V_{DS} \geq V_{GS} - V_{TH}$

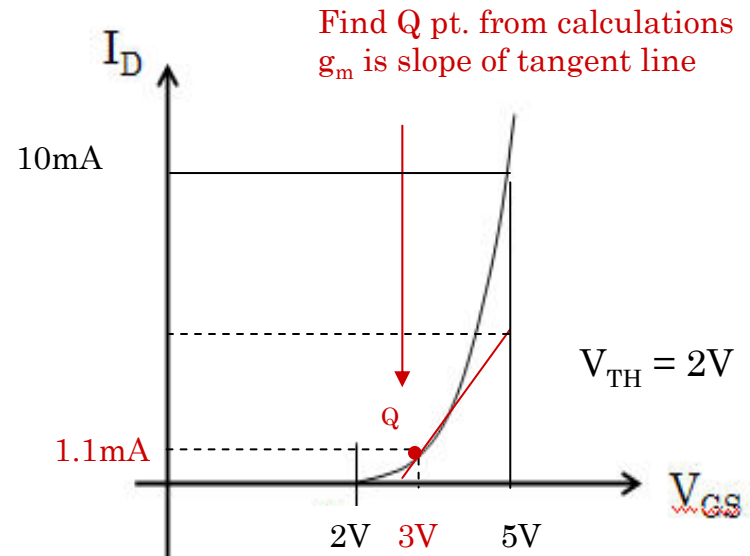
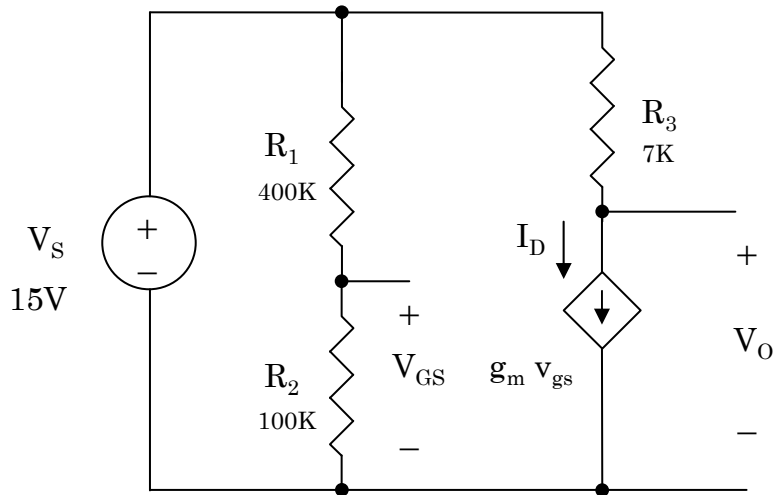


$$V_i = 0.1 \sin(2 \pi 1000 t)$$



MOSFETs

- Linear Circuits
 - Example – Amplifier
 - ◆ DC Analysis – Find Q Point (Cont.)



Find V_{GS} → Simple voltage divider:

$$V_{GS} = V_S R_2 / (R_1 + R_2) = (15) (100K) / (500K) = 3V > V_{TH} \rightarrow \text{Operating in Active Region}$$

$$I_D = K/2 (V_{GS} - V_{TH})^2$$

From curve, find:

$$10mA = K/2 (5 - 2)^2 \rightarrow K = 2.2E-3$$

Plug in K, V_{GS} , & V_{TH} to find I_D at Q:

$$I_D = (2.2E-3)/2 (3 - 2)^2 = 1.1mA$$

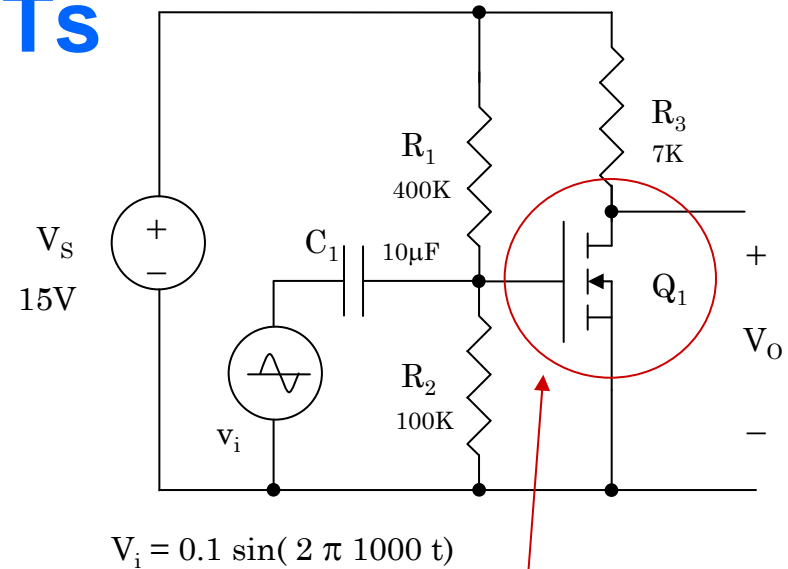
$$V_O = V_S - (I_D R_3) = 15 - 7.7 = 7.3V$$

Now find g_m from curve at Q point:

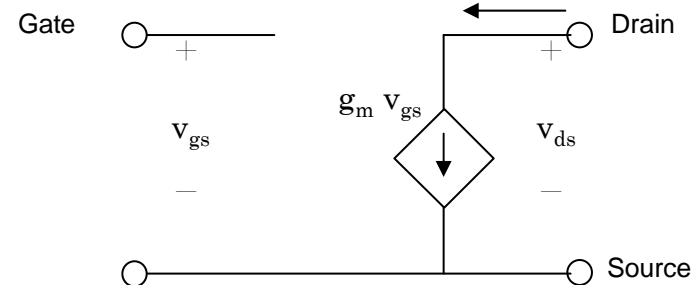
$$g_m = \left. \frac{\partial I_D}{\partial V_{GS}} \right|_Q \approx 5 \text{ mA} / 2.5V = 2E-3$$

MOSFETs

- Linear Circuits (Continued)
 - Example – Amplifier (Cont.)
 - ◆ AC Analysis – Find the Gain
 - Remove all DC sources
 - > Voltage sources → short
 - > Current sources → open
 - Insert AC model
 - Analyze circuit
 - Find Gain

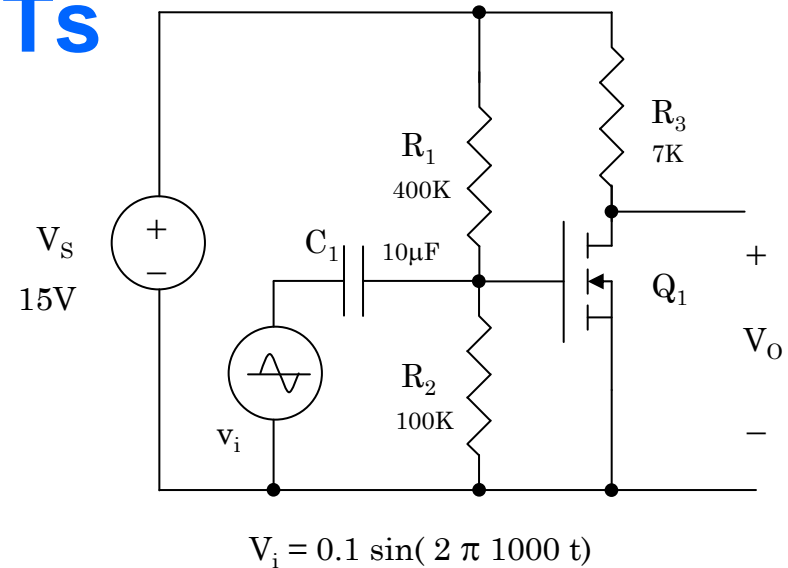


Mid-Frequency AC Model

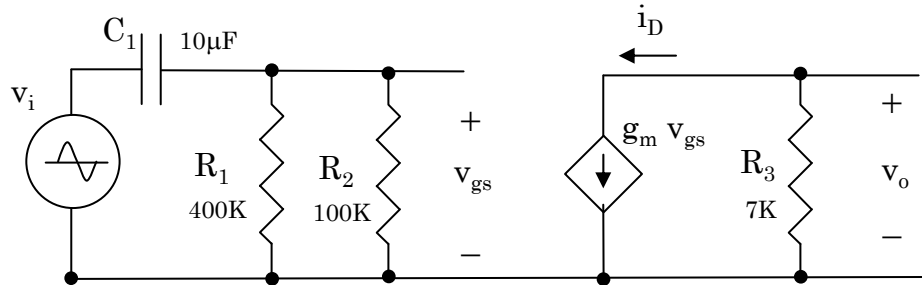


MOSFETs

- Linear Circuits (Continued)
 - Example – Amplifier (Cont.)
 - AC Analysis



Equivalent Circuit at Mid-Frequency with Transistor Model



Find v_{gs} → Node Equation:

$$[v_{gs} / R_1] + [v_{gs} / R_2] + [(v_{gs} - v_i) / (Z_{C1})] = 0$$

$$Z_{C1} = 1 / (j \omega C_1)$$

$$v_{gs} [1/R_1 + 1/R_2 + (j \omega C_1)] = v_i (j \omega C_1)$$

$$v_{gs} = \frac{v_i (j \omega C_1) (R_1 R_2)}{R_1 + R_2 + (j \omega C_1 R_1 R_2)}$$

$$v_{gs} \approx v_i$$

Find v_o → Node Equation:

$$[v_o / R_3] + i_d = 0$$

$$[v_o / R_3] + g_m v_{gs} = 0$$

$$v_{gs} = v_i, \quad g_m = 2E-3 \text{ (from DC analysis)}$$

$$v_o = -g_m v_i R_3 = - (0.1) (2E-3) = -1.4$$

$$\frac{v_o}{v_i} = -g_m R_3 = -14$$

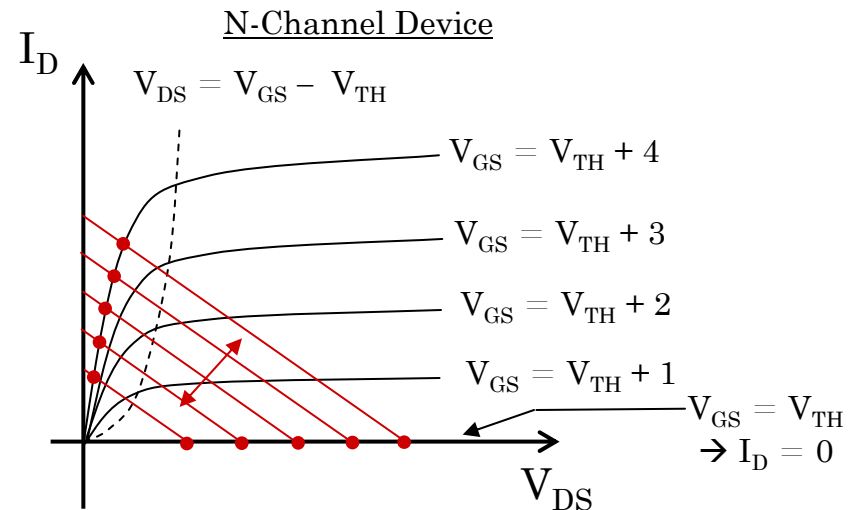
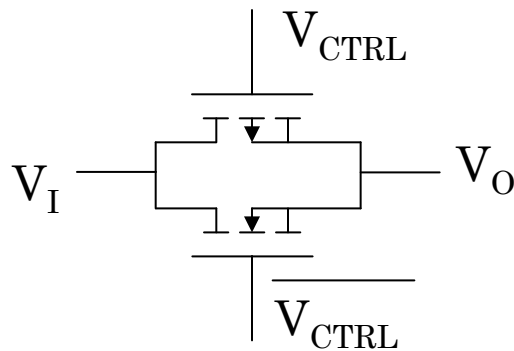
$$v_o(t) = 7.3 - 1.4 \sin(2\pi 1000 t)$$

⇒ **Output is sum of DC + AC parts**

MOSFETS

■ Analog Switches

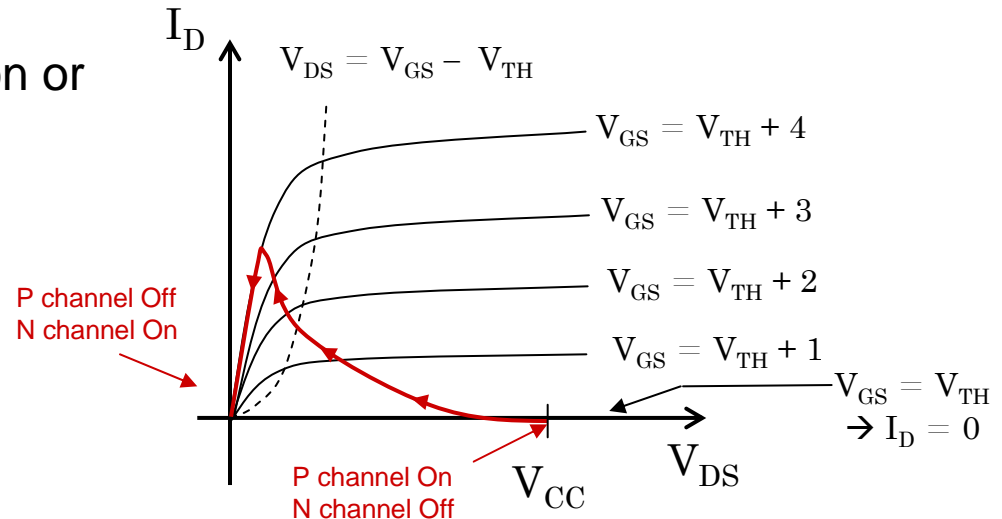
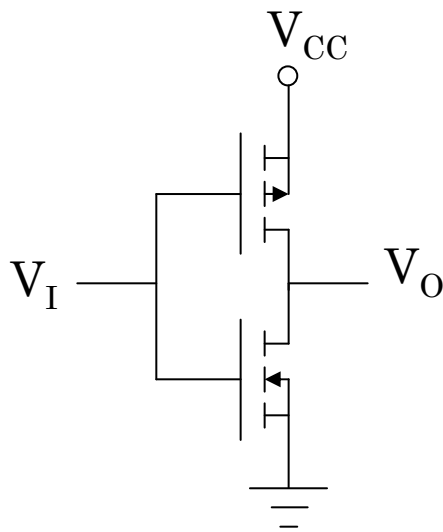
- Principle: Operate either in ohmic region, or at $I_D = 0$



- ◆ Load line moves, depending on V_{DS}
- ◆ But operate either on $V_{GS} = V_{GS,MAX}$ or on $V_{GS} = V_{TH}$

MOSFETS

- Digital Logic → CMOS
 - Also operating either full on or full off, not in between
 - Consider an inverter



Only have current flow during switching
(Approximate Off-to-On transition showing)

Switching times: ~nSec → pSec

When not switching → No current → Low power

- ◆ When $V_I = V_{CC}$, Q_2 ON, Q_1 OFF → $V_O = 0V$
- ◆ When $V_I = 0V$, Q_2 OFF, Q_1 ON → $V_O = V_{CC}$

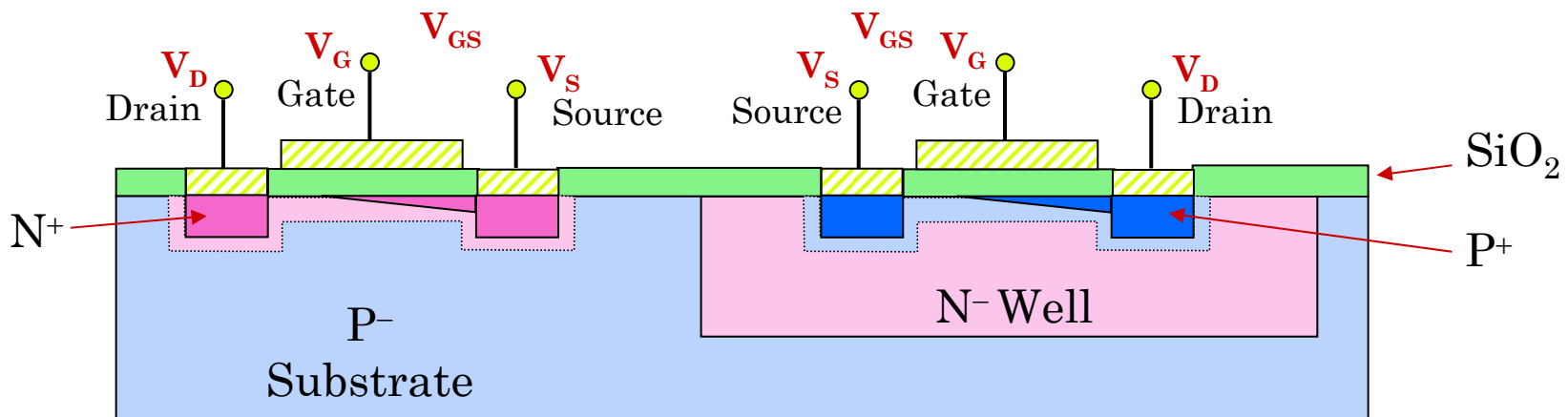
V_{IN}	V_{OUT}
L	H
H	L

CMOS

■ Motivation

- For many circuits (amplifiers, switches, digital logic), it is useful to have both N-channel and P-channel devices on the same substrate
 - ◆ How is this done? → P wells & N wells

■ Basic Construction

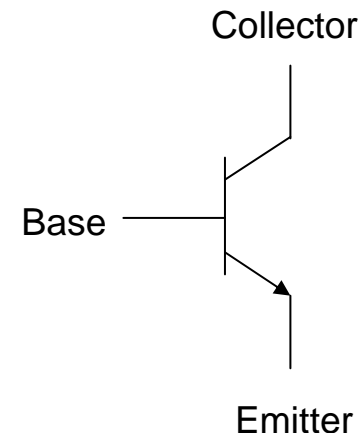


⇒ **Basis for modern IC fabrication technologies**

Bipolar Transistors

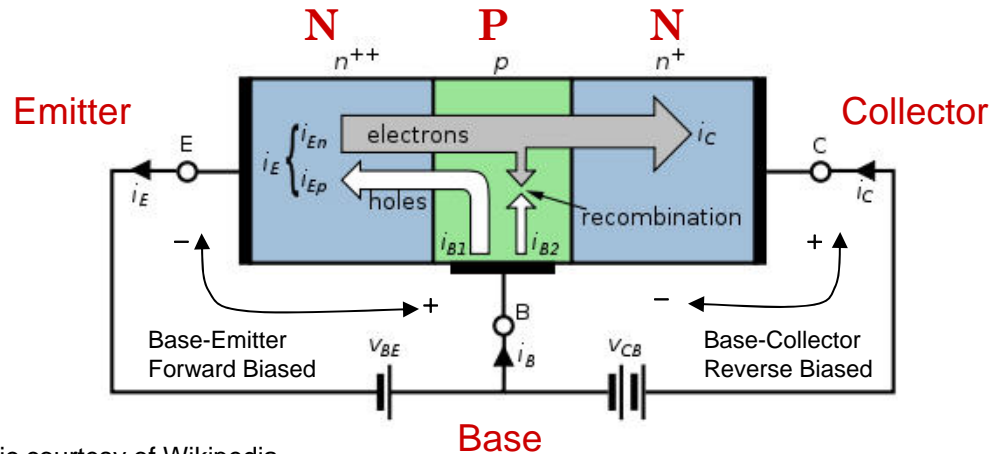
- Introduction

- Bipolar Junction Transistors (BJTs) are 3-terminal devices, where the current flow between two of the terminals (Collector & Emitter) is controlled by injecting charge into the third terminal (Base), which creates diffusion currents between the two active terminals.
 - ◆ Current flow is achieved by diffusion currents between the two highly-doped active terminals (Collector & Emitter)
 - ◆ Charge carriers are minority carriers (p-type → electrons, n-type → holes)
 - ◆ Current flow is bi-directional (both electrons and holes participate)



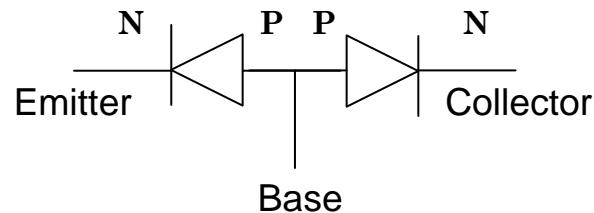
Bipolar Transistors

- Basic Construction – NPN Transistor
 - Conceptual construction



Graphic courtesy of Wikipedia

- ⇒ **Looks like two back-to-back diodes**
- ⇒ **Base-Emitter junction is forward-biased**
- ⇒ **Base-Collector junction is reverse biased**

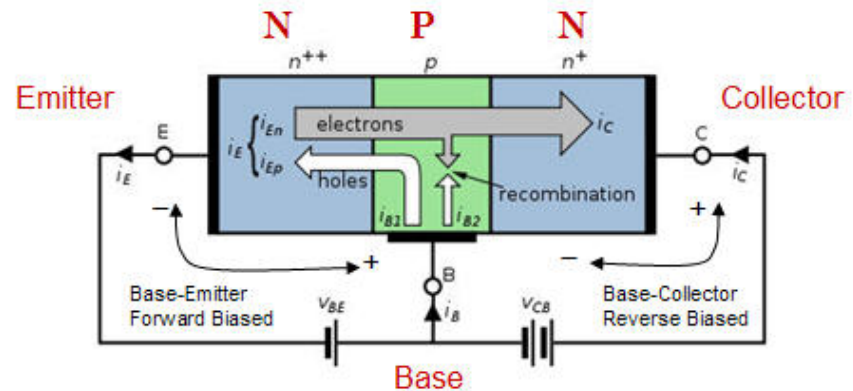


Bipolar Transistors

- Basic Construction – NPN Transistor

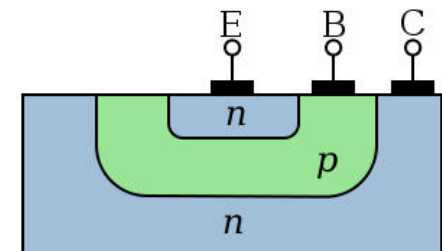
- How does it work?

- Start by injecting a hole into the Base from external source
- Extra hole in Base attracts electrons from the Emitter
- As electrons enter Base from Emitter, they are swept through the base by the strong electric field seen by the reverse-biased Base-Collector junction
- Generally, N electrons are swept through from Emitter to Collector before hole in Base can migrate to Emitter
 - Gives Current Gain $\beta = I_C / I_B$
- Some holes in Base recombine in Base with electrons from Emitter
- Most holes make it to the Emitter



Graphic courtesy of Wikipedia

Typical Construction



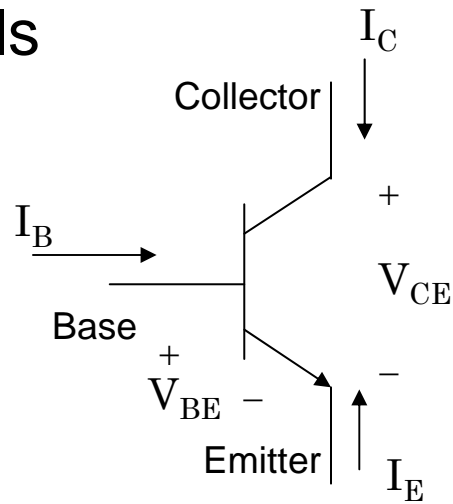
Graphic courtesy of Wikipedia

- ⇒ The unique construction of the junctions, along with the special doping levels, make this work
- ⇒ Can have NPN, or PNP Transistors

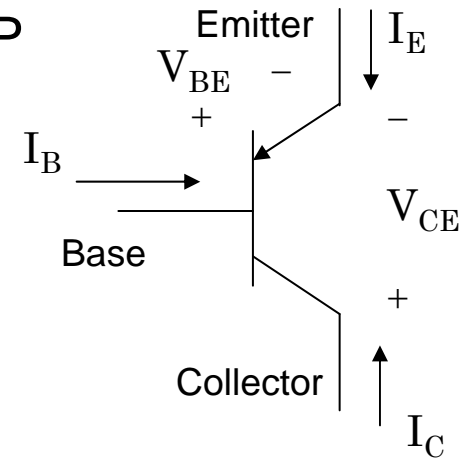
Bipolar Transistors

- Symbols

- NPN

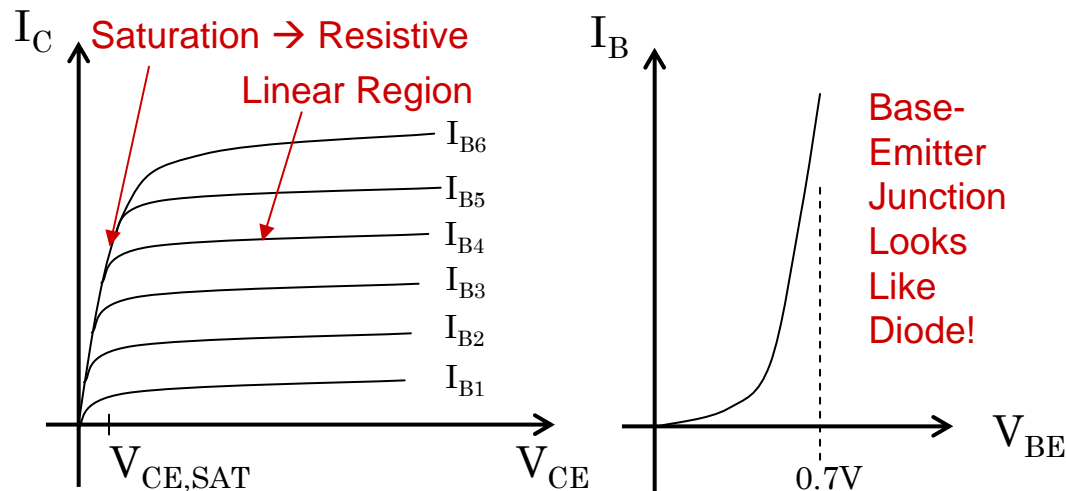


- PNP

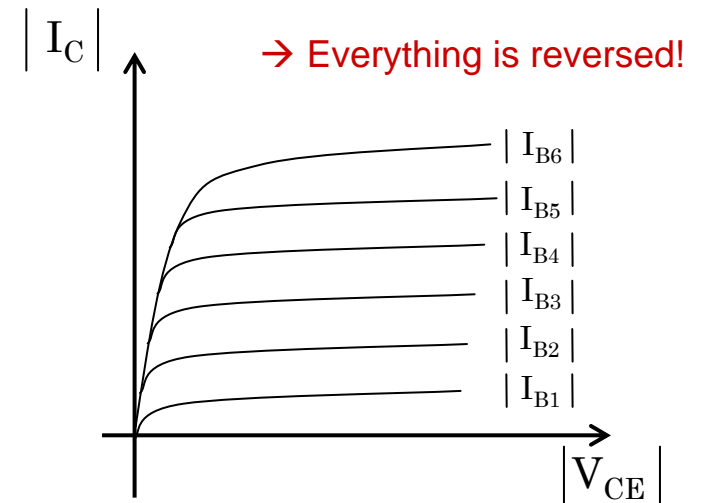


- IV Characteristics

- NPN



- PNP

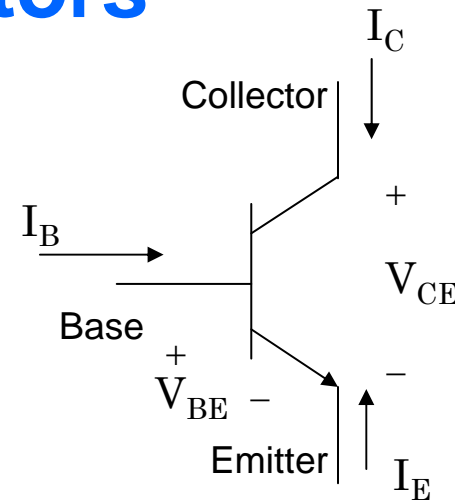
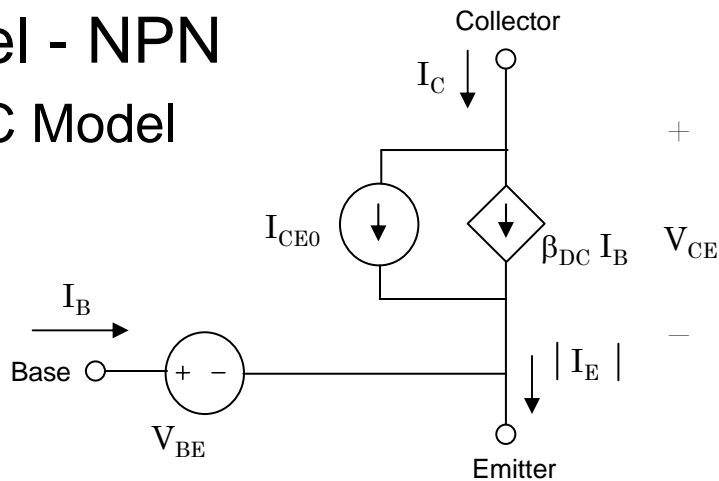


Bipolar Transistors

- Model - NPN

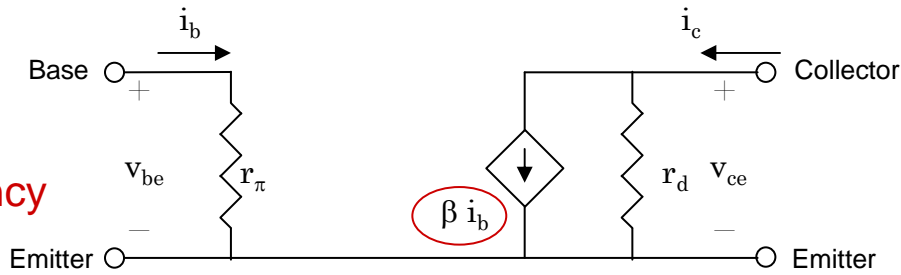
- DC Model

Model For Linear Region

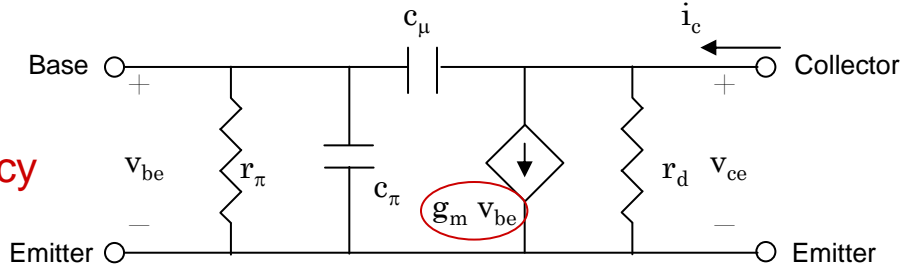


- AC Models – Hybrid Pi

Mid Frequency

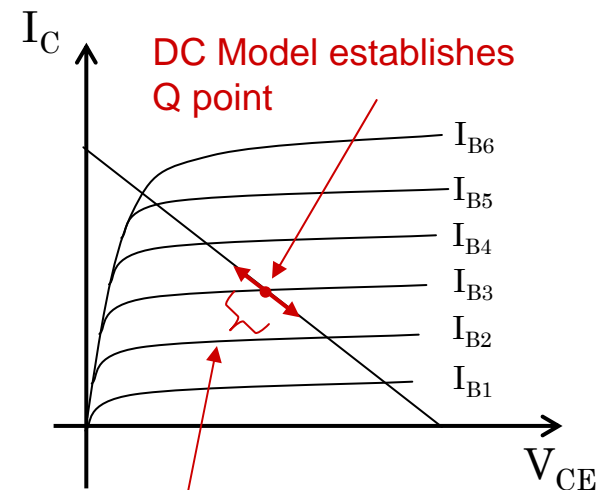


High Frequency



$$g_m v_{be} = \beta i_b$$

Generally have a "Load Line":



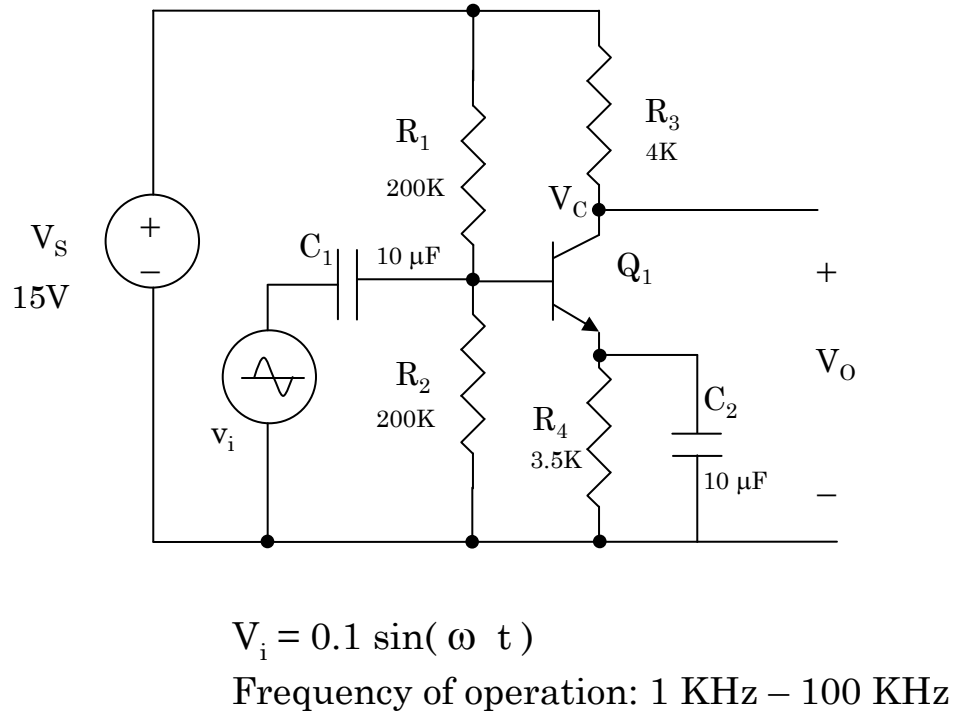
DC Model establishes Q point

AC Model determines excursion

Bipolar Transistors

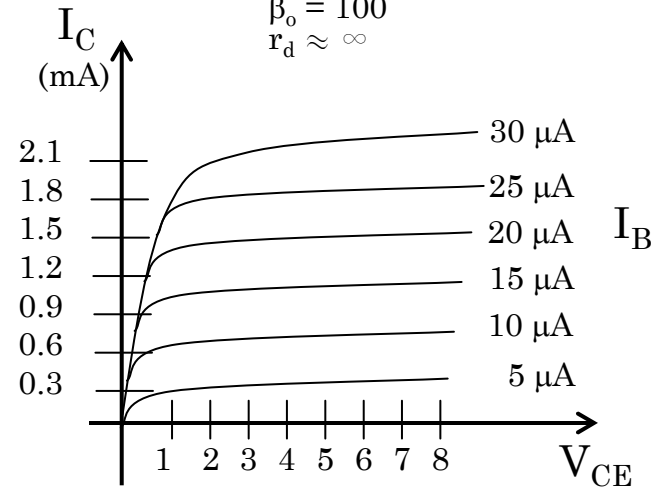
- Linear Circuits

- Example: NPN Common Emitter Amplifier



Data from Manufacturer

$I_{CEO} \approx 0$
 $V_{BE} = 0.7 \text{ V}$
 $r_{\pi} = 23\text{K}$
 $\beta_{DC} = 70$
 $\beta_o = 100$
 $r_d \approx \infty$

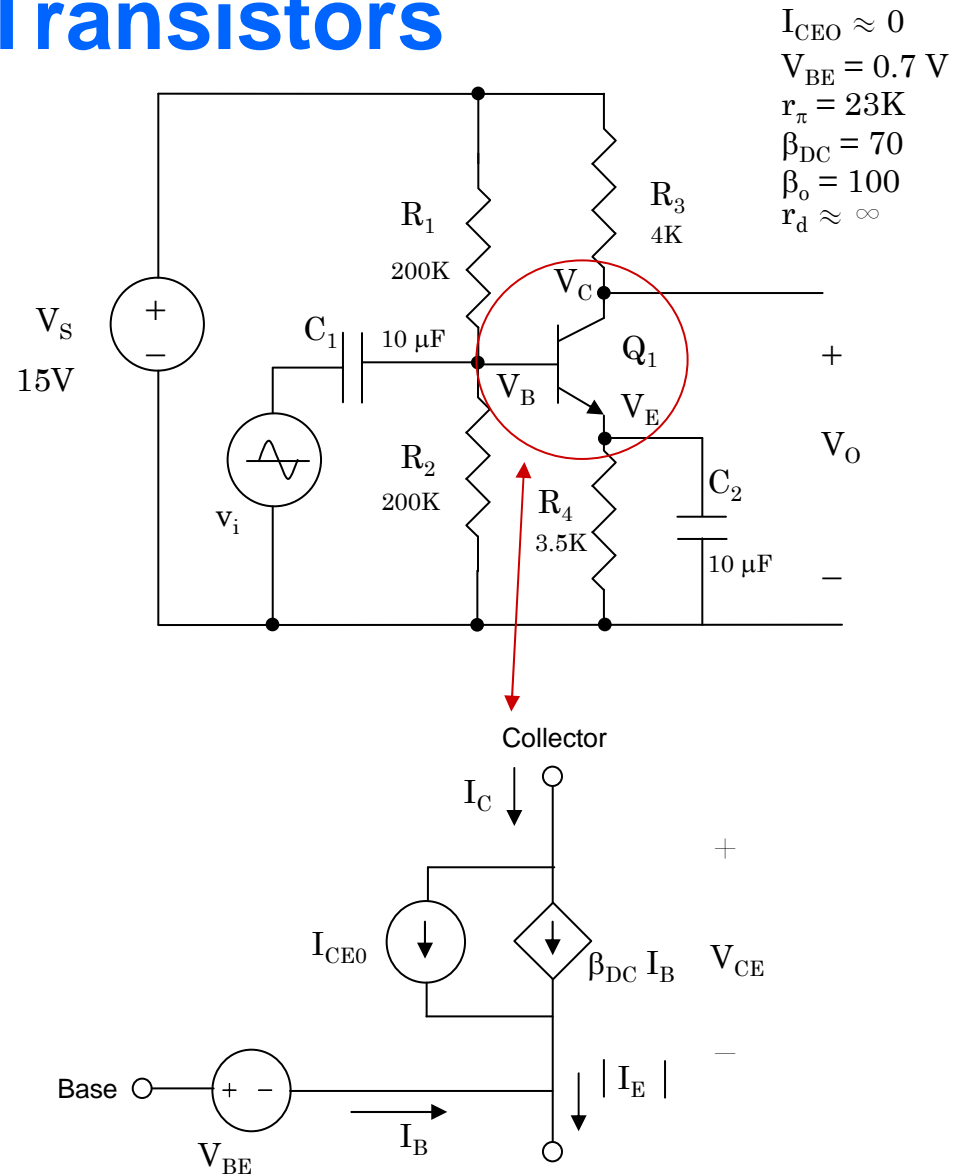


Bipolar Transistors

- Linear Circuits (Cont.)
 - Example (Cont.):
NPN Common Emitter Amplifier

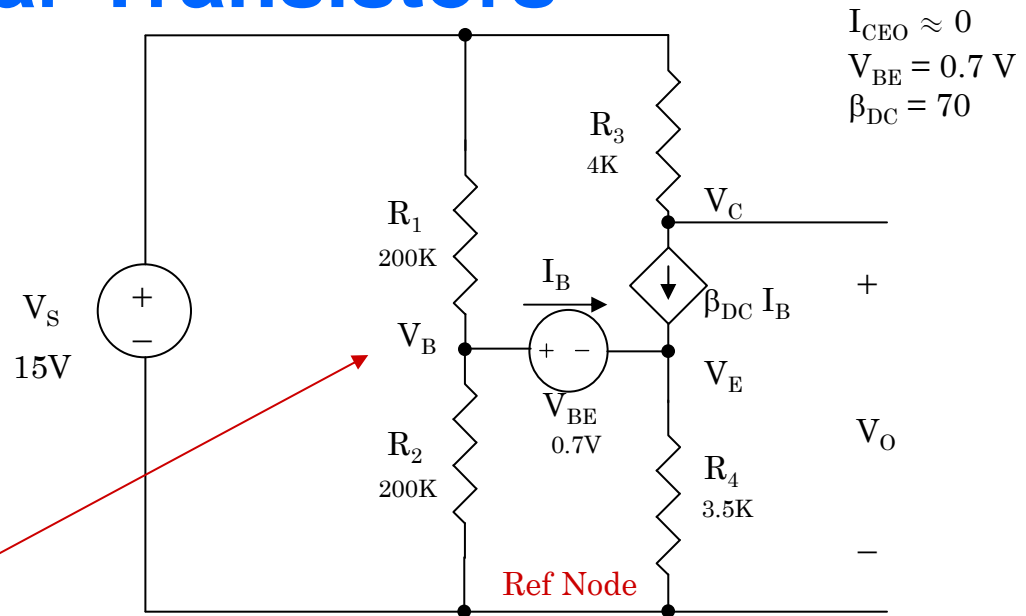
- DC Analysis – Find Q Point
 - Remove all L's & C's
 - Capacitors open
 - Inductors short
 - Remove all time-dependent sources
 - Voltage sources shorted
 - Current sources open
 - Insert DC model
 - Analyze circuit
 - Find operating point

DC Model for the NPN Transistor



Bipolar Transistors

- Linear Circuits
 - Example (Cont.):
 - ◆ DC Analysis
 - Find Q Point



$I_{CEO} \approx 0$
 $V_{BE} = 0.7 \text{ V}$
 $\beta_{DC} = 70$

Write node equation at V_B :

$$[(V_B - V_S) / R_1] + [V_B / (R_2)] + I_B = 0$$

At node V_E :

$$V_E = (I_B + \beta_{DC} I_B) R_4 = I_B (1 + \beta_{DC}) R_4$$

Then, noting that V_B and V_E are related:

$$\begin{aligned}
 V_E &= V_B - V_{BE} = V_B - 0.7 \\
 &= I_B (1 + \beta_{DC}) R_4
 \end{aligned}$$

$$I_B = (V_B - 0.7) / [(1 + \beta_{DC}) R_4]$$

Solving:

$$V_B [1/R_1 + 1/ R_2 + 1/[(1 + \beta_{DC}) R_4]] = V_S/R_1 + 0.7 / [(1+\beta_{DC})R_4]$$

Plugging in values, find:

$$V_B = 5.56\text{V}$$

$$V_E = V_B - 0.7 = 4.86\text{V}$$

$$I_B = (V_B - 0.7) / [(1+\beta_{DC}) R_4] = 19.6 \mu\text{A}$$

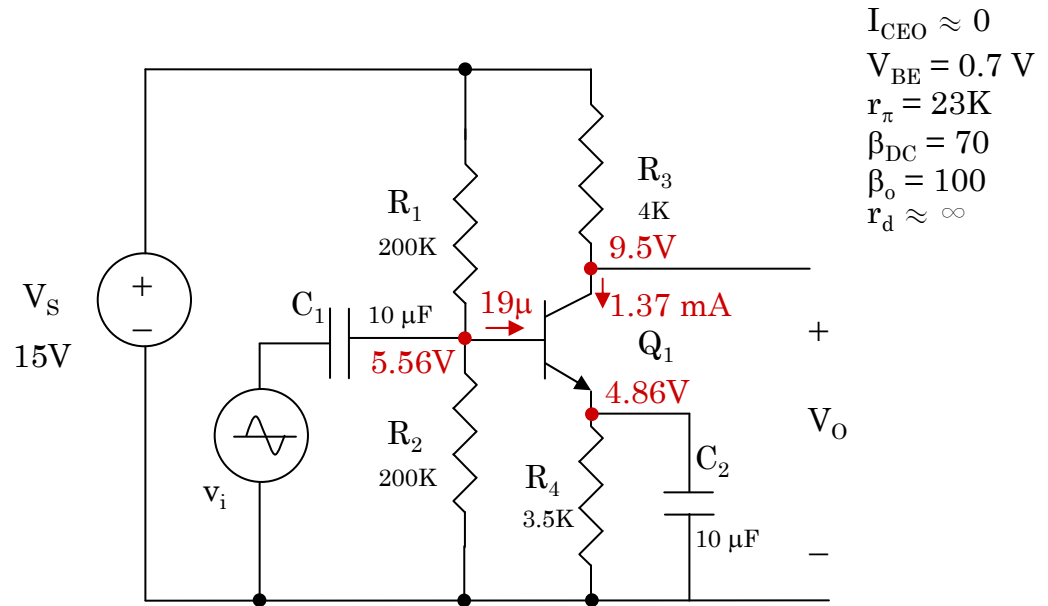
$$V_C = V_S - [\beta_{DC} I_B R_3] = 9.5\text{V}$$

$$V_{CE} = V_C - V_E = 4.64\text{V}, \quad I_C = \beta_{DC} I_B = 1.37 \text{ mA}$$

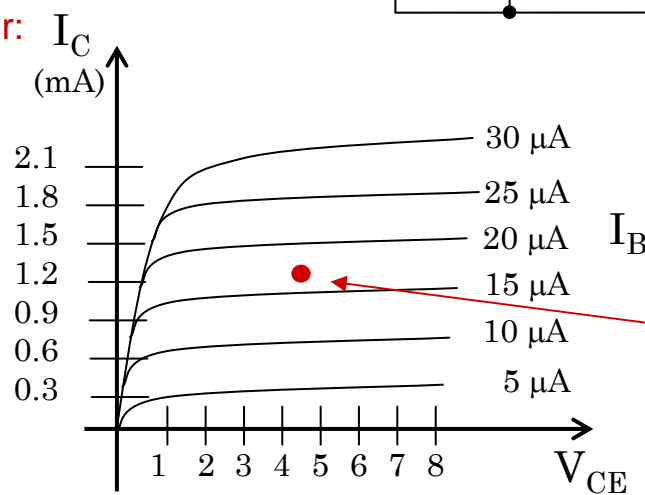
Bipolar Transistors

- Linear Circuits

- Example (Cont.)
 - ◆ DC Analysis (Cont.)
 - Check results



Curve from Mfgr:



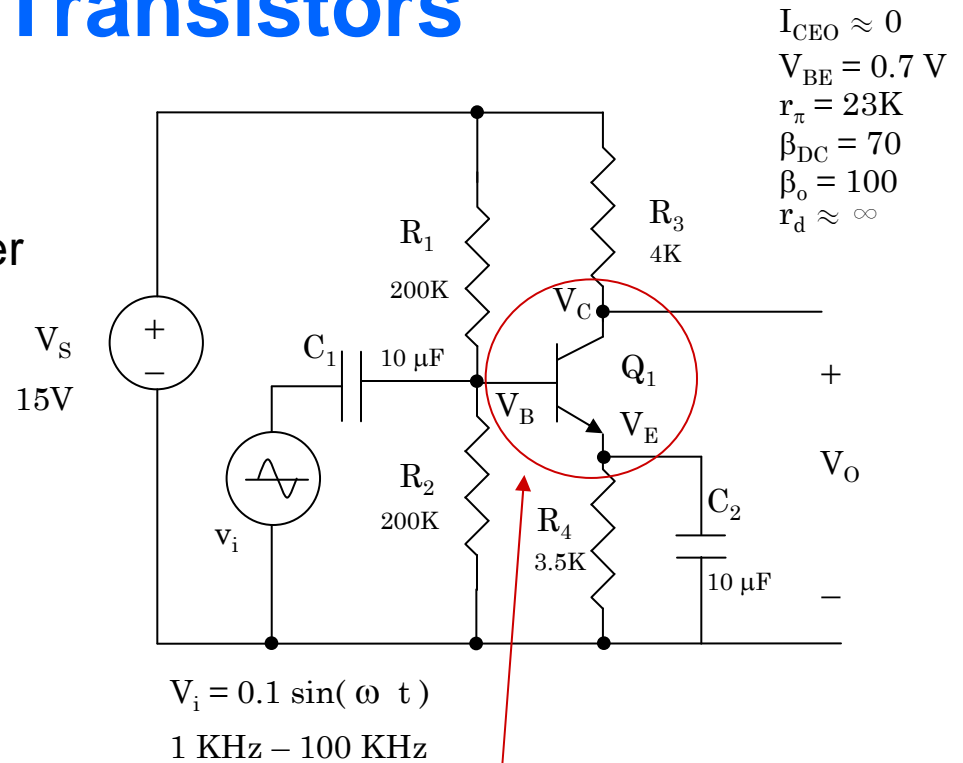
Approximate operating point
 → Good place to operate for a linear amplifier

Bipolar Transistors

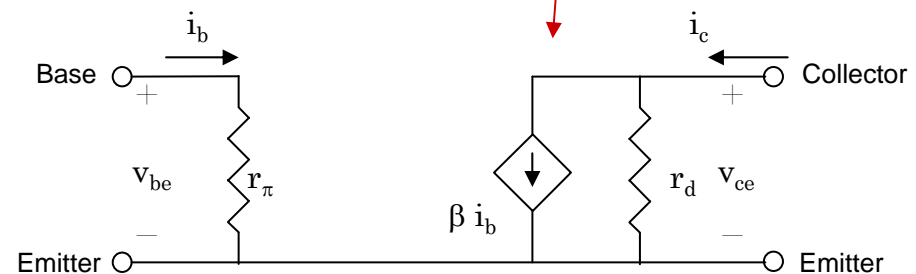
Linear Circuits

- Example (Cont.):
NPN Common Emitter Amplifier

- ◆ AC Analysis – Find the Gain
 - Remove all DC sources
 - > Voltage sources → short
 - > Current sources → open
 - Insert AC model
 - Analyze circuit
 - Find Gain



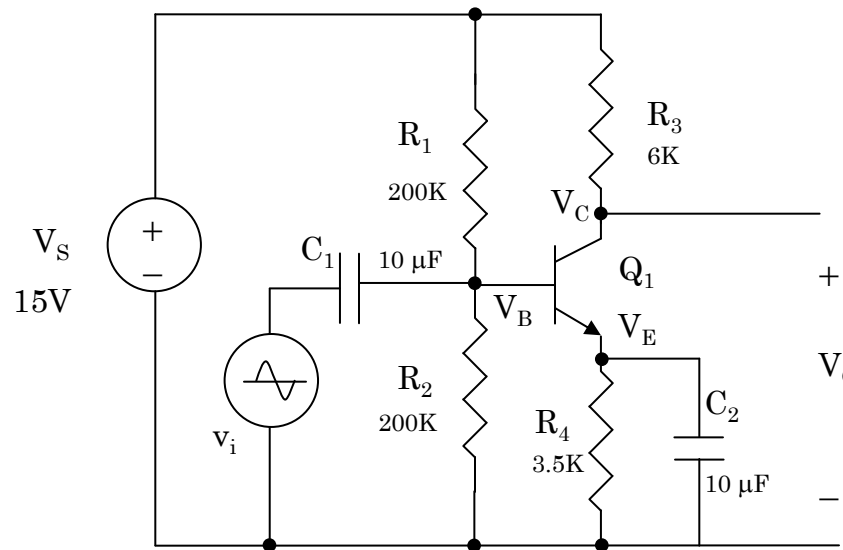
Mid-Frequency AC Model for the NPN Transistor



Bipolar Transistors

- Linear Circuits
 - Example (Cont.):
 - ◆ AC Analysis (Continued)

$I_{CEO} \approx 0$
 $V_{BE} = 0.7 \text{ V}$
 $r_{\pi} = 23\text{K}$
 $\beta_{DC} = 70$
 $\beta_o = 100$
 $r_d \approx \infty$



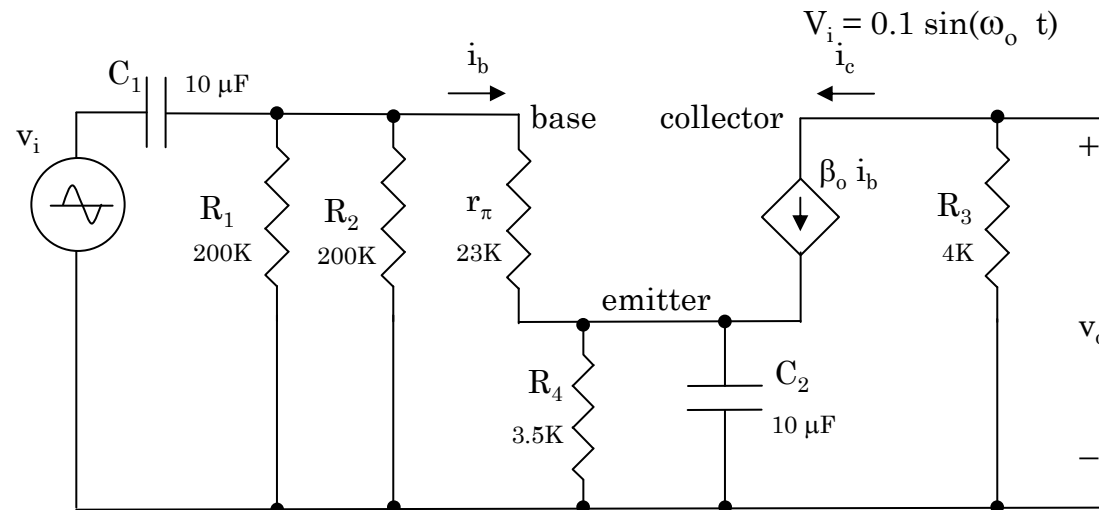
More complicated...

But, for mid frequencies, it turns out that can treat C_1 & C_2 as short circuits

Why?...

Impedances are small compared to R_1, \dots, R_4 at frequencies $> 1000 \text{ Hz}$

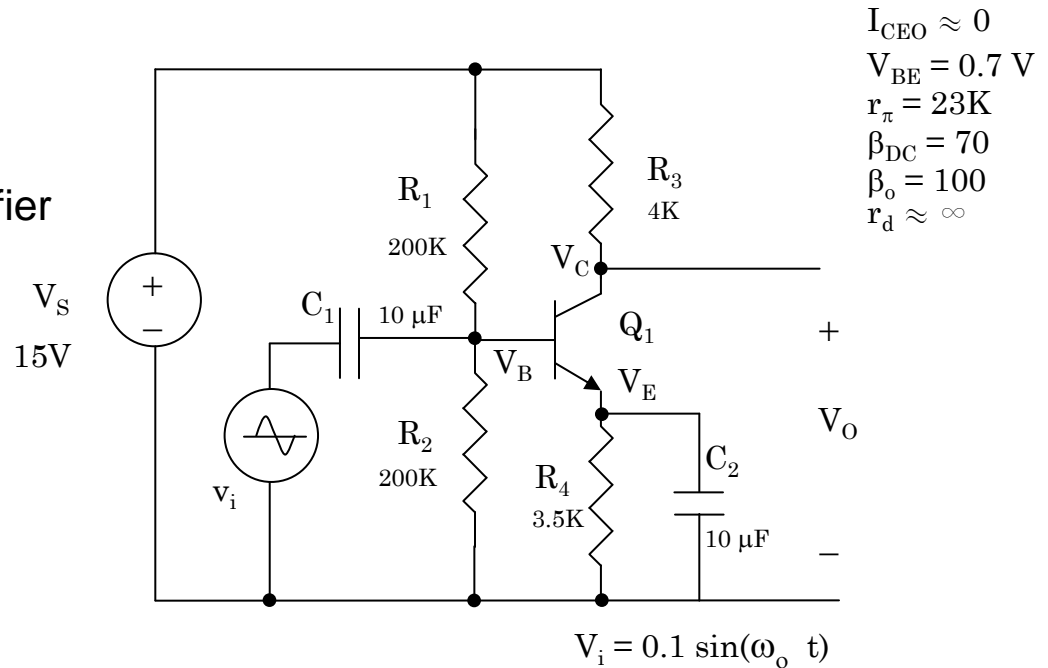
⇒ Can Simplify...



Bipolar Transistors

Linear Circuits

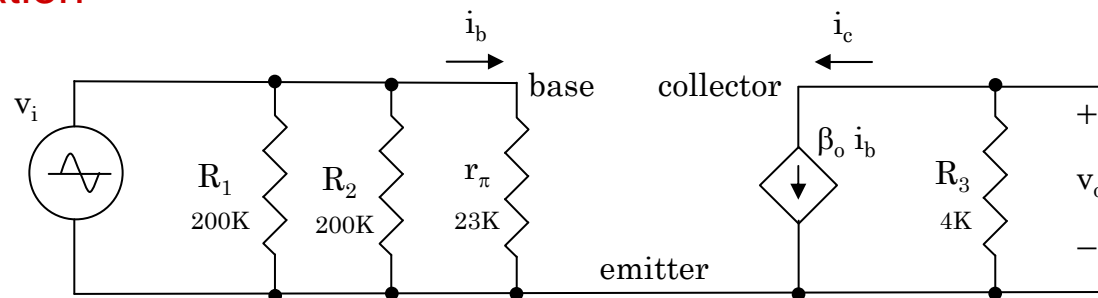
- Example (Cont.):
NPN Common Emitter Amplifier
- ◆ AC Analysis (Continued)



Treating C_1 & C_2 as short circuits:

- ⇒ Much simpler
- ⇒ Need only 1 node equation to solve!

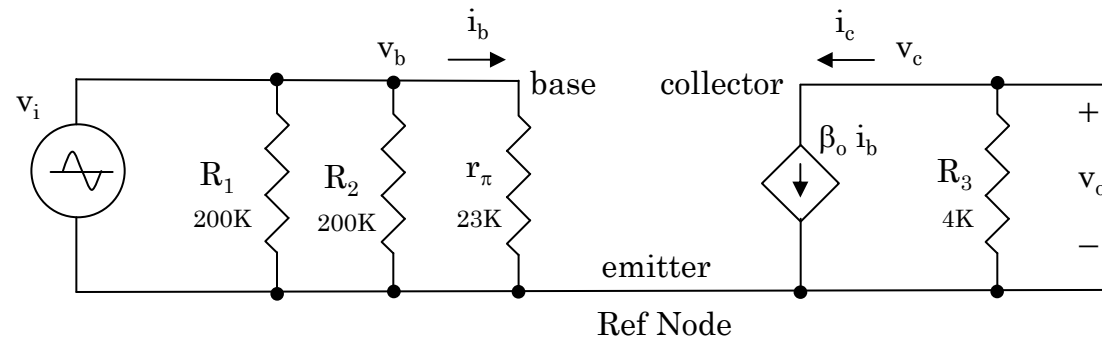
Equivalent Circuit at Mid-Frequency with Transistor Model



Bipolar Transistors

Linear Circuits

- Example (Cont.): NPN Common Emitter Amplifier
 - ♦ AC Analysis (Continued)



$I_{CEO} \approx 0$
 $V_{BE} = 0.7 \text{ V}$
 $r_{\pi} = 23\text{K}$
 $\beta_{DC} = 70$
 $\beta_o = 100$
 $r_d \approx \infty$

$$i_b = v_i / r_p$$

$$v_o = -\beta_o i_b R_3$$

$$= -\beta_o R_3 v_i / r_p$$

$$\frac{v_o}{v_i} = -\beta_o R_3 / r_{\pi} = -\beta_o R_3 / r_{\pi} = -17.4$$

⇒ Valid over mid-frequencies
~1 KHz – 100 KHz

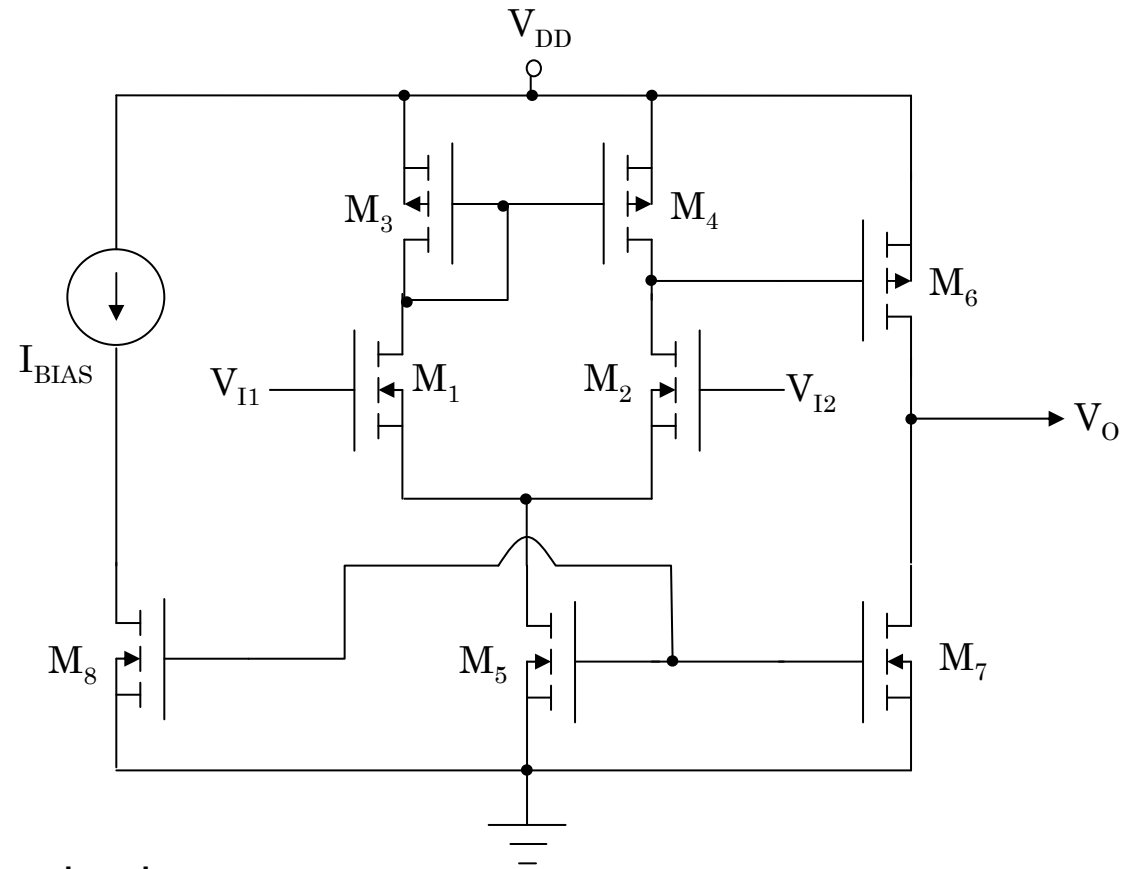
$$\text{For: } v_i(t) = 0.1 \sin(2\pi 10,000 t) \rightarrow v_o(t) = 9.5 - 1.74 \sin(2\pi 10,000 t)$$

⇒ Output is sum of DC + AC parts

CMOS Analog Circuits

■ A Basic CMOS, Differential, 1-Stage Amplifier

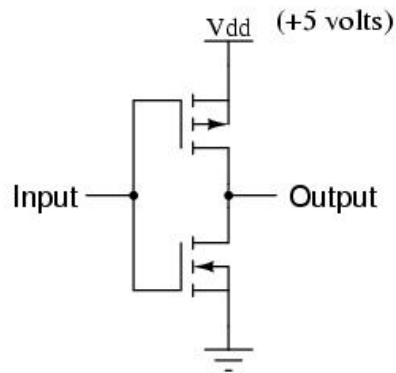
- Uses P channel and N channel devices
- No resistors!
- Simple circuit can have gains ~ 1000
- **→ ASICS**
 - ◆ Designer chooses transistor width and length of channel
- Uses same principles introduced in this lecture
- Each transistor has a role...
- Generally use SPICE to simulate, but first design pass uses hand calculations



CMOS Digital Circuits

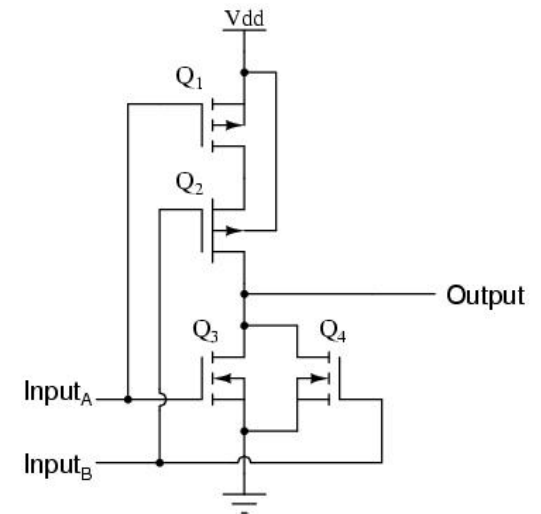
■ Inverter

INPUT		OUTPUT
A		NOT A
0		1
1		0



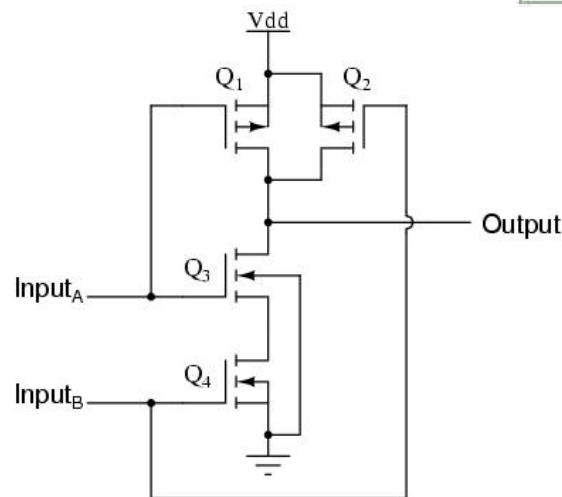
■ NOR

INPUT		OUTPUT
A	B	A NOR B
0	0	1
0	1	0
1	0	0
1	1	0



■ NAND

INPUT		OUTPUT
A	B	A NAND B
0	0	1
0	1	1
1	0	1
1	1	0



⇒ **These are the basic building blocks for flip-flops, counters, registers Programmable Logic, Microprocessors,**

Images from allaboutcircuits.com

**Thank You
for your Attention!**

**I hope that you enjoyed the course
and found it useful!**